

# Designing Future VLSI Systems with Monolithically Integrated Silicon-Photonics

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University of California, Berkeley



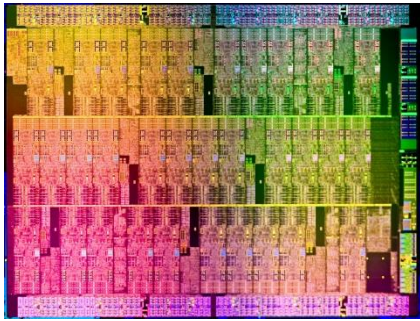
**SSCS DL Lecture**  
**University of Texas, Austin**  
**November, 2013**

# Acknowledgments

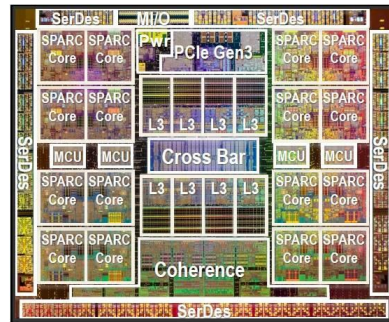
- Milos Popović (Boulder), Rajeev Ram, Michael Watts, Hanqing Li (MIT), Krste Asanović (UC Berkeley)
- Jason Orcutt, Jeffrey Shainline, Christopher Batten, Ajay Joshi, Anatoly Khilo
- Mark Wade, Karan Mehta, Erman Timurdogan, Jie Sun, Cheryl Sorace, Josh Wang
- Michael Georgas, Jonathan Leu, Benjamin Moss, Chen Sun, Yu-Hsin Chen
- Yong-Jin Kwon, Scott Beamer, Yunsup Lee, Andrew Waterman, Miquel Planas
- Roy Meade, Gurtej Sandhu and Fab12 team (Zvi, Ofer, Daniel, Efi, Elad, ...)
- DARPA, Micron, NSF and FCRP IFC
- IBM Trusted Foundry, CNSE Albany, Solid-State Circuits Society

# Chip design is going through a change

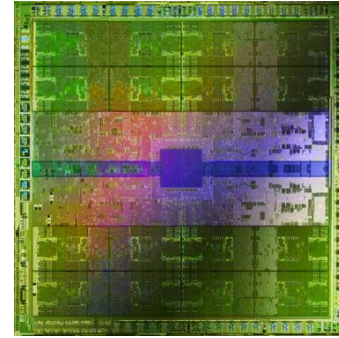
- Already have more devices than can use at once
- Limited by power density and bandwidth



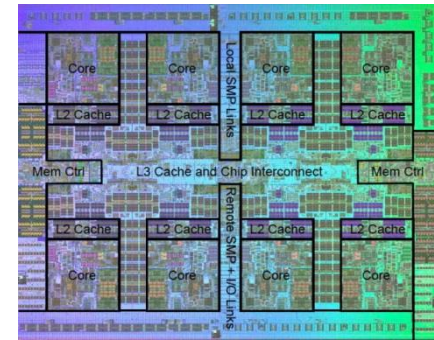
Intel Knights Corner  
50 cores, 200 Threads



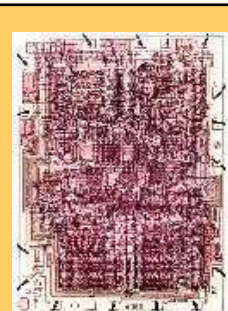
Oracle T5  
16 cores, 128 Threads



Nvidia Fermi  
540 CUDA cores



IBM Power 7  
8 cores, 32 threads

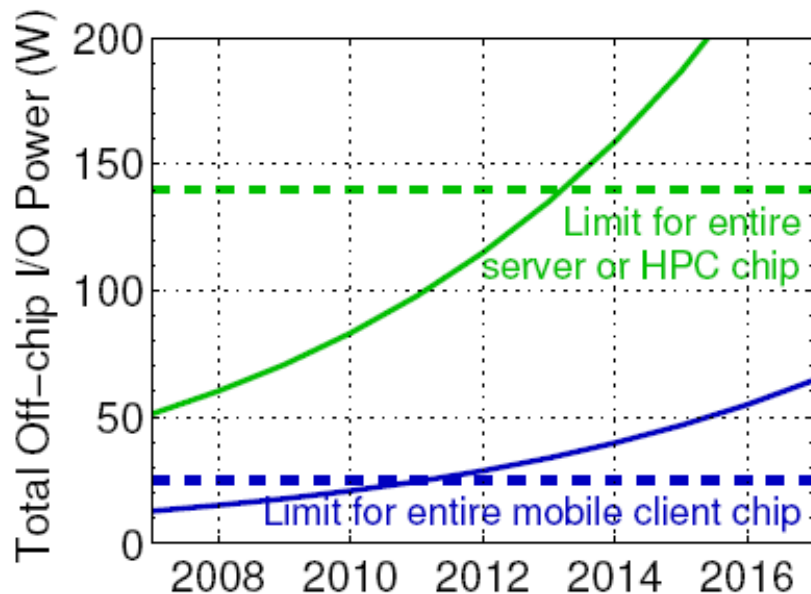
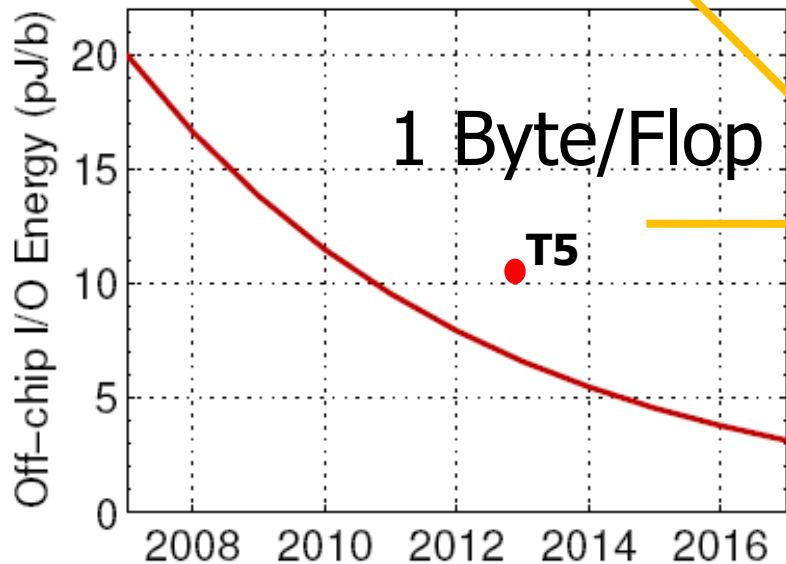
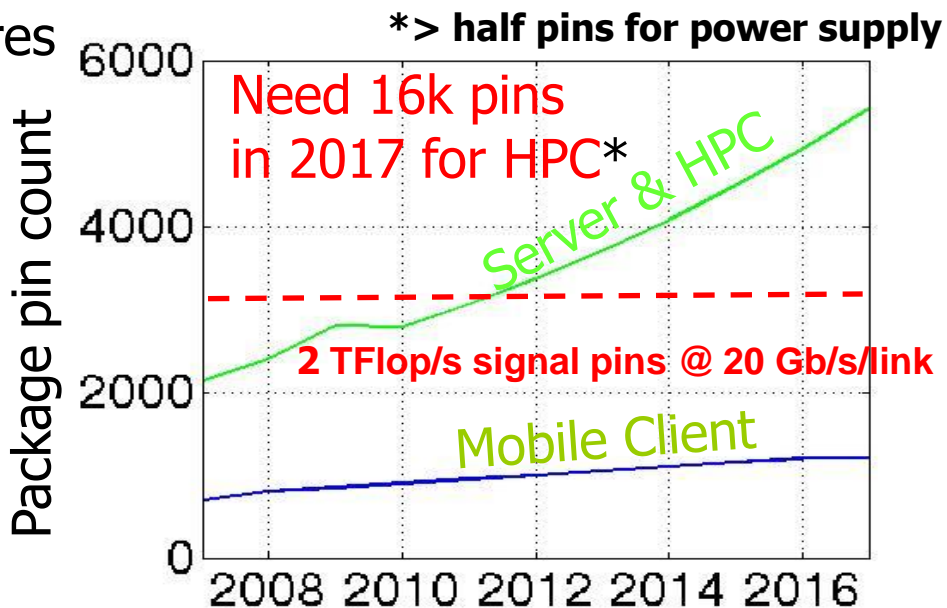
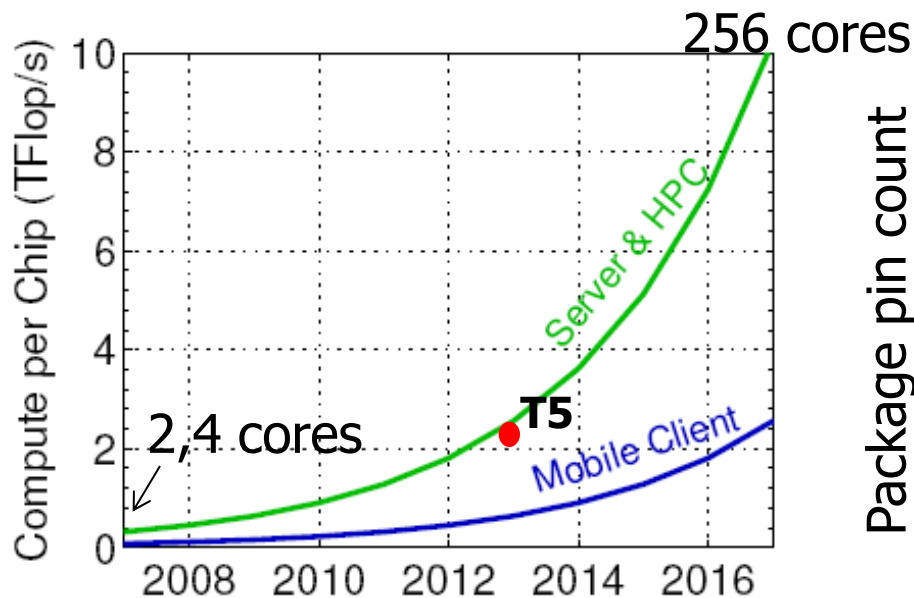


Intel 4004 (1971):  
4-bit processor,  
2312 transistors,  
~100 KIPS,  
10 micron PMOS,  
11 mm<sup>2</sup> chip

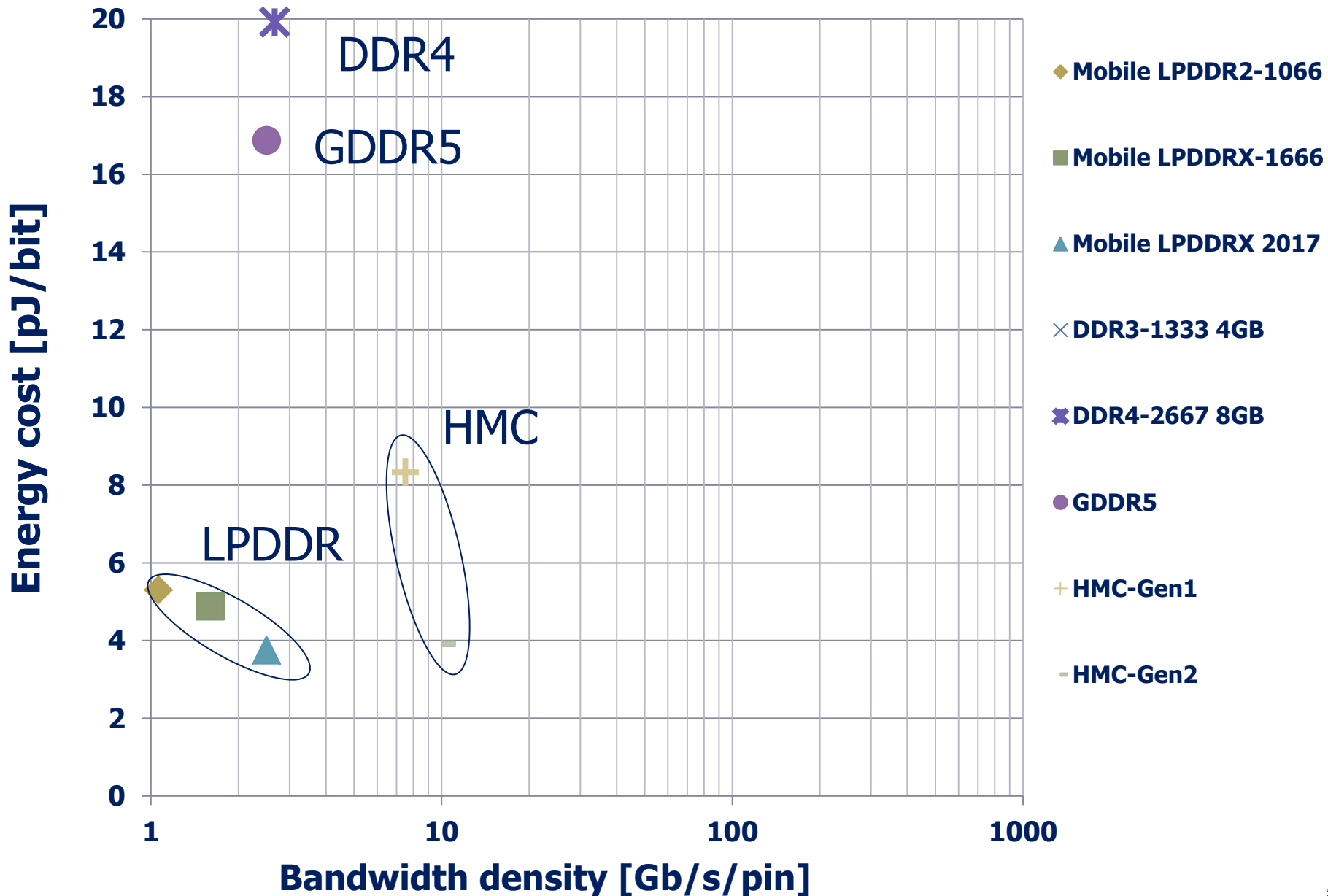
1000s of  
processor  
cores and  
accelerators  
per die

***“The Processor is  
the new Transistor”  
[Rowen]***

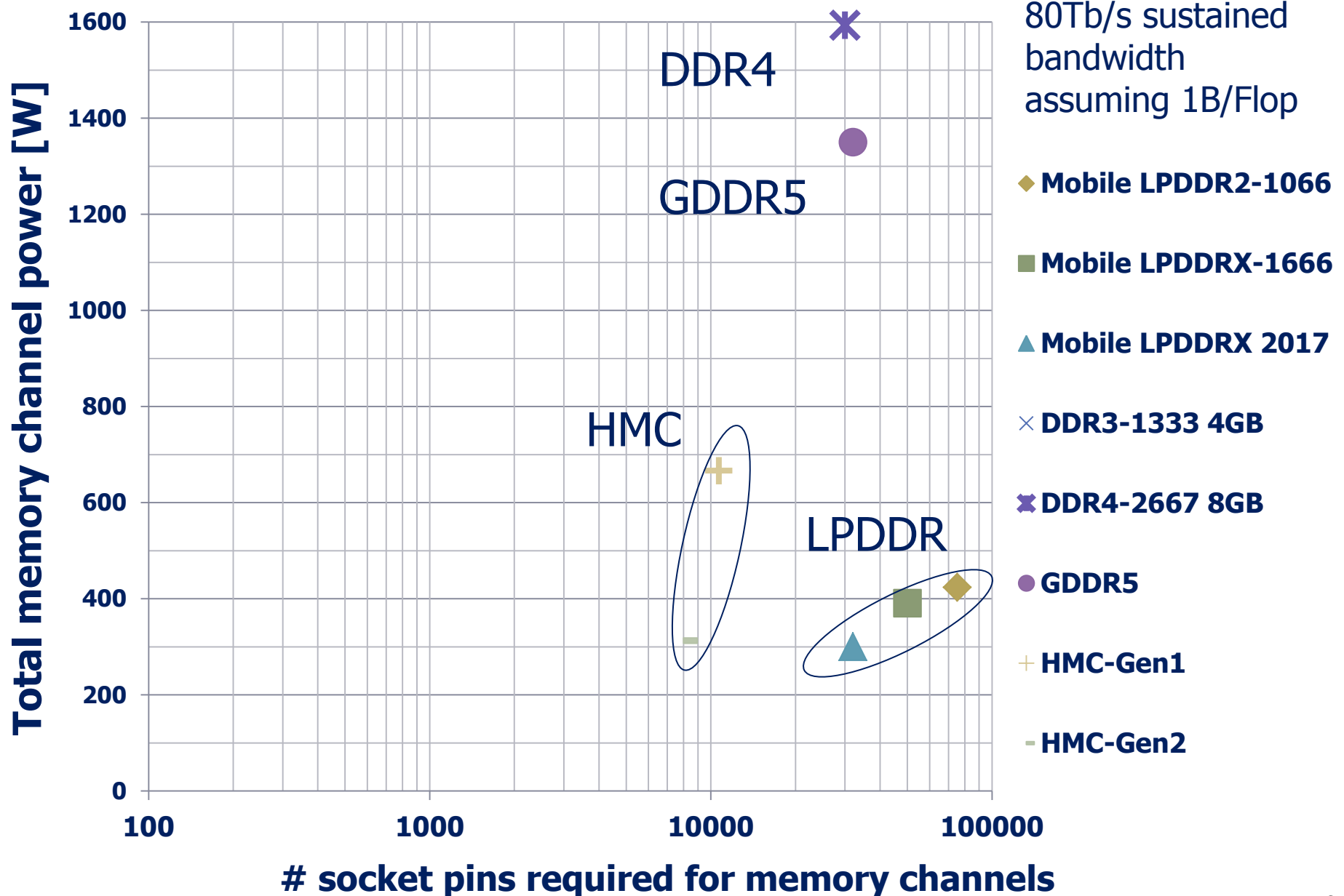
# Bandwidth, pin count and power scaling



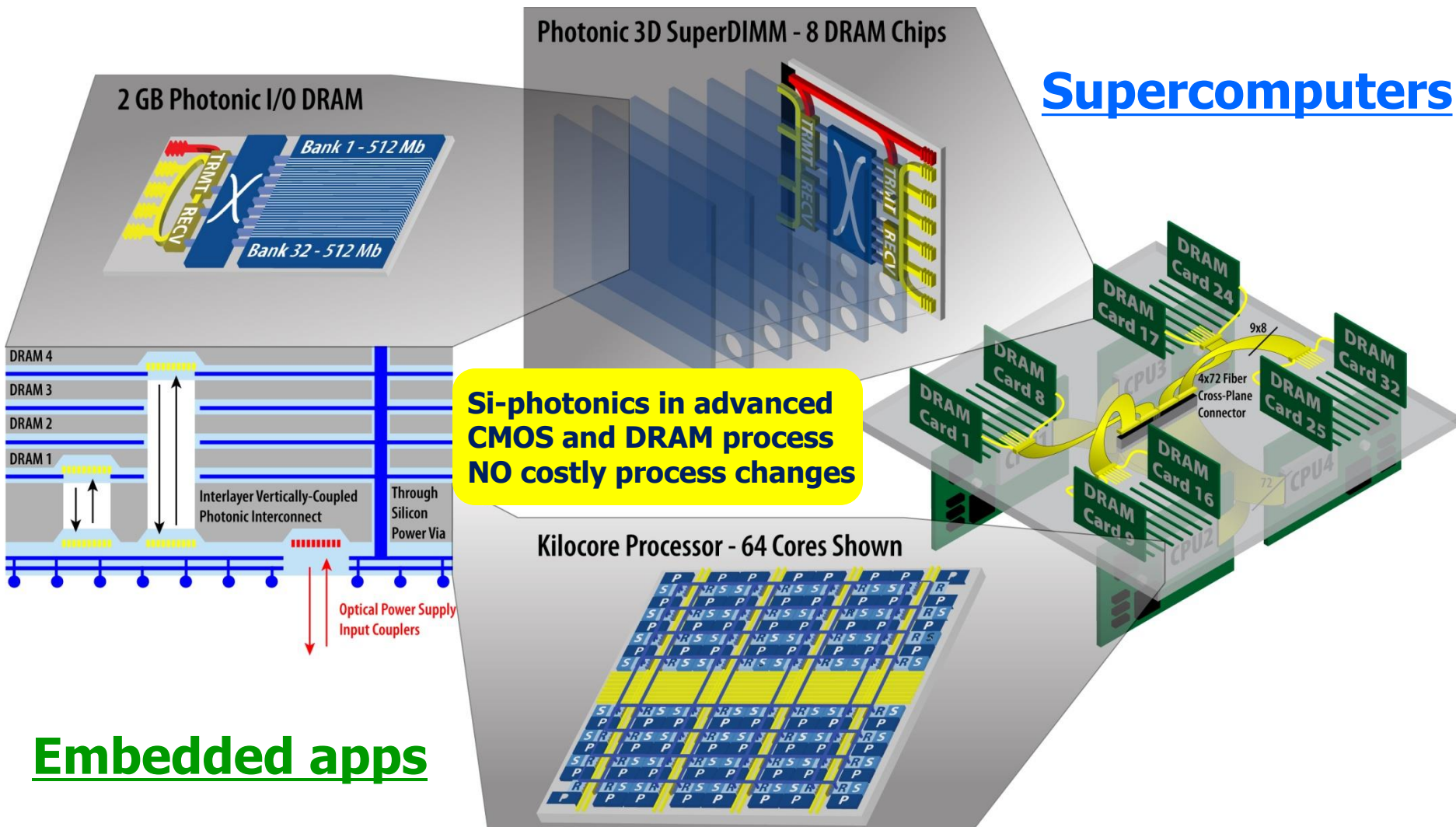
# Memory interface scaling problems: Energy-cost and bandwidth density



# Power and pins required for 10TFlop/s



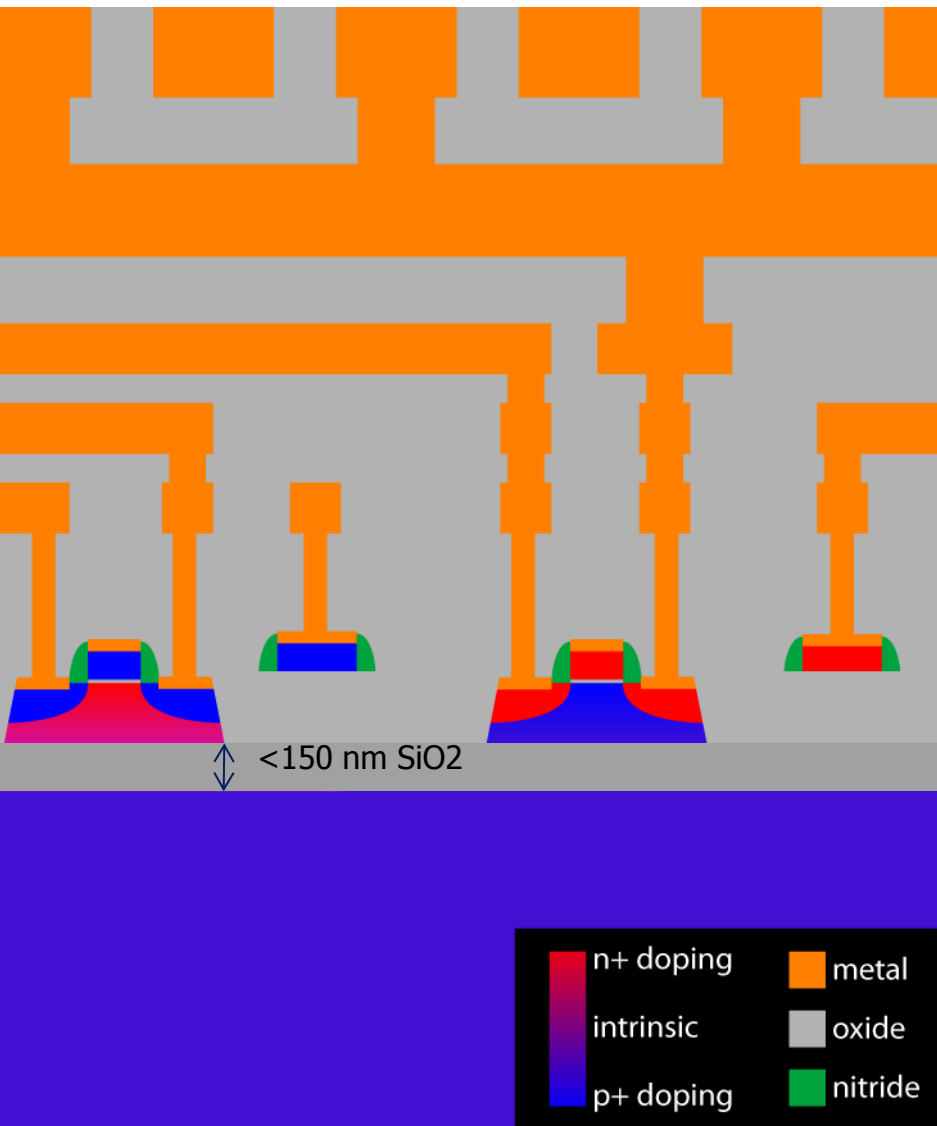
# Monolithic Si-Photonics for core-to-core and core-to-DRAM networks



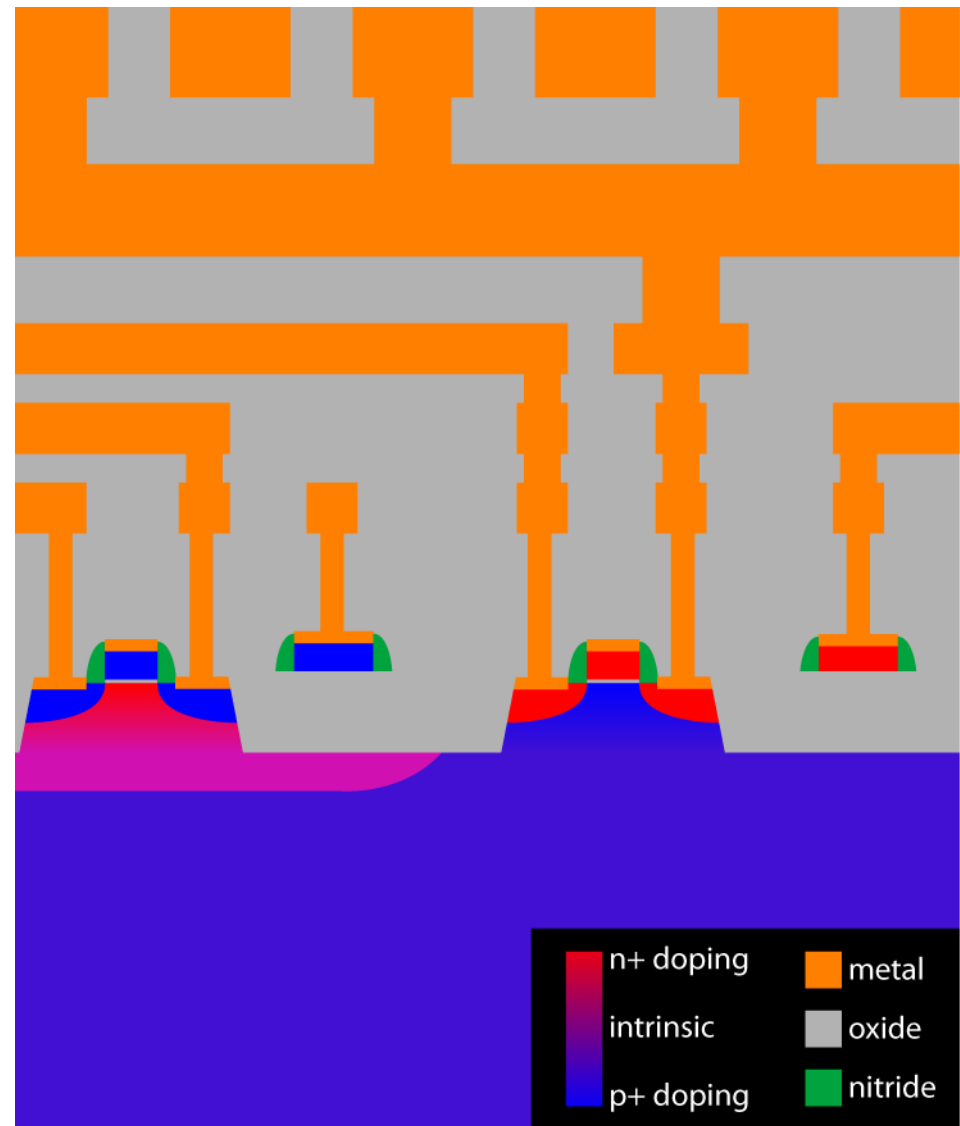
Bandwidth density – need dense WDM

Energy-efficiency – need monolithic integration

# Monolithic CMOS photonic integration



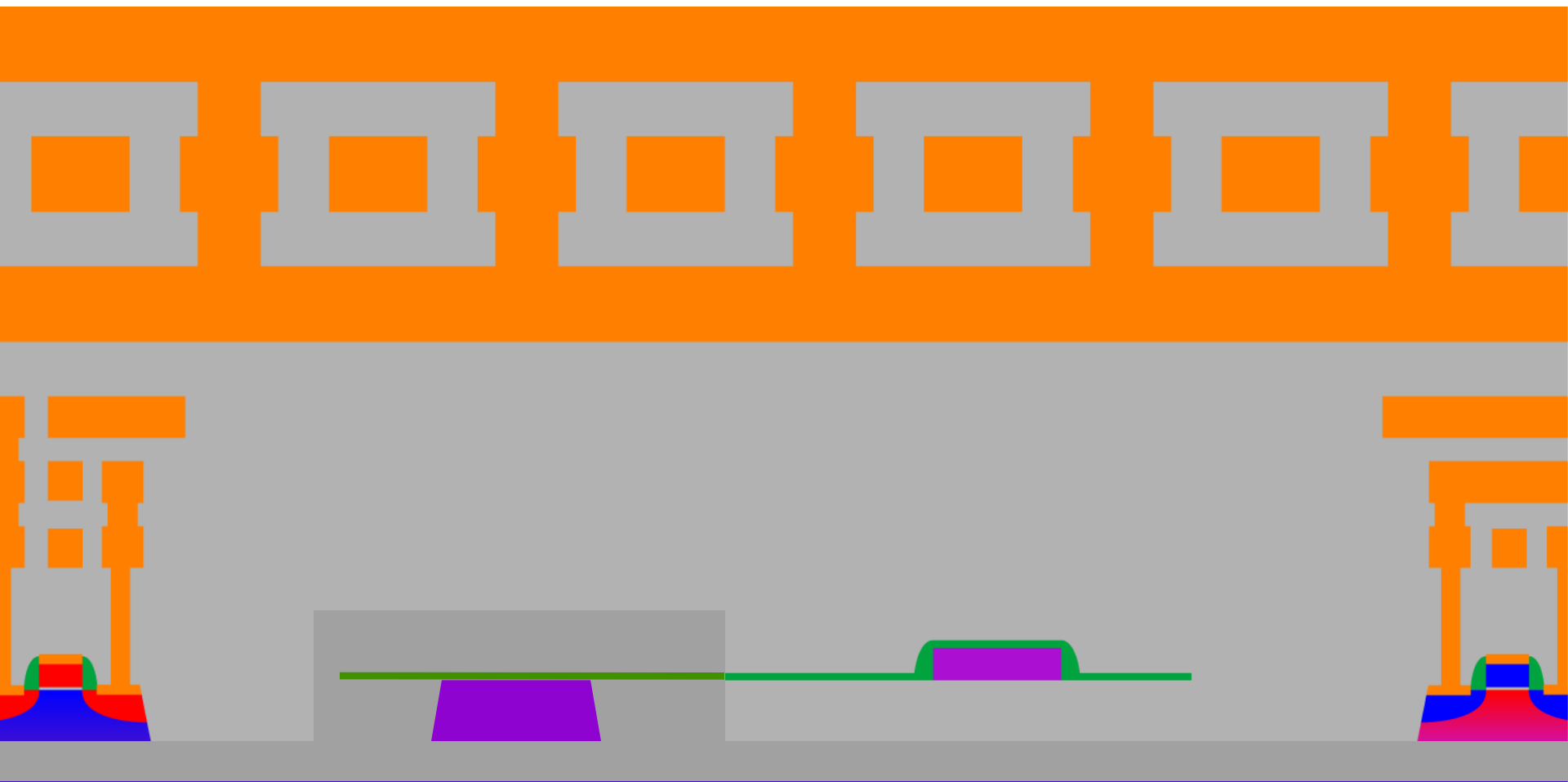
Thin BOX SOI CMOS Electronics



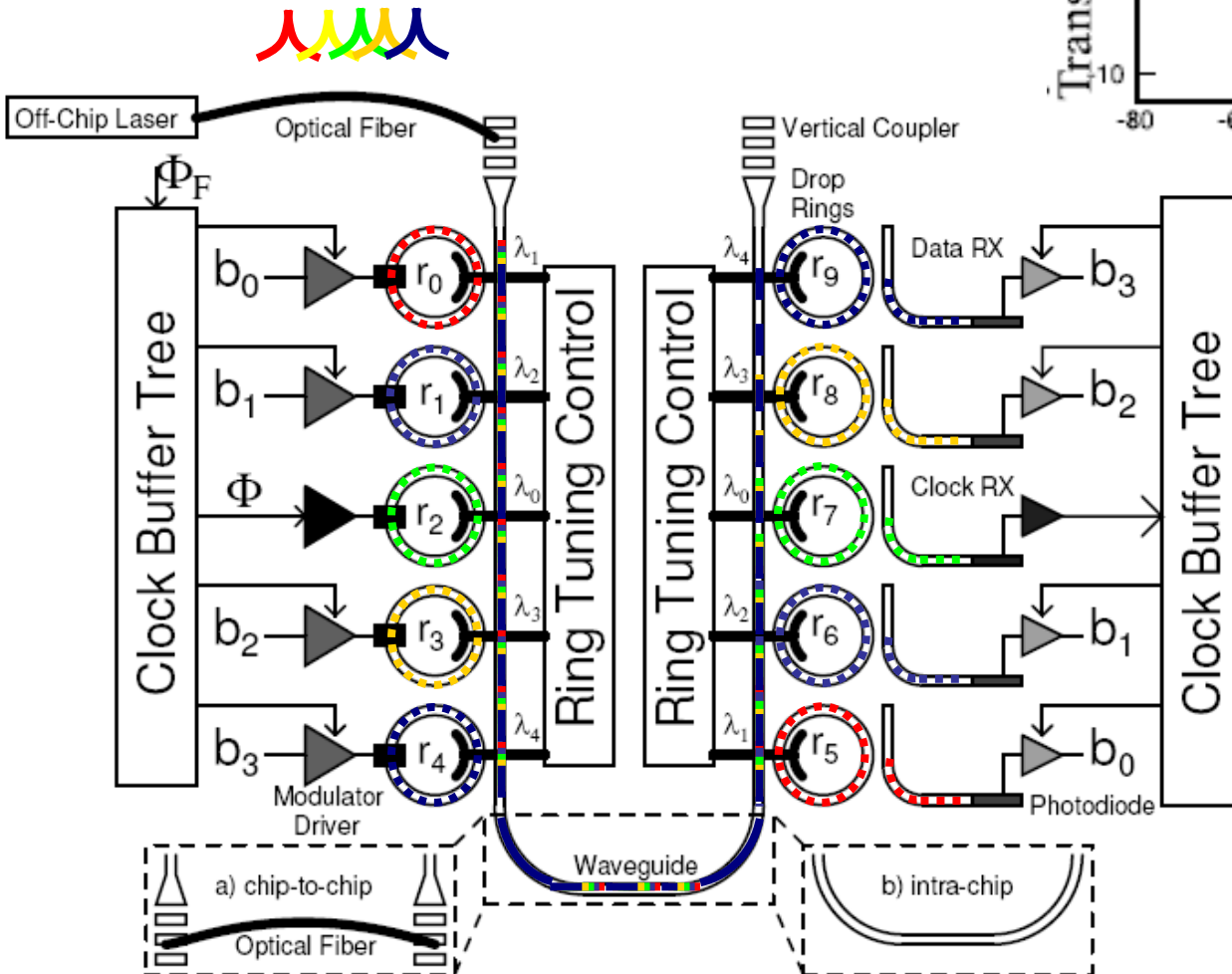
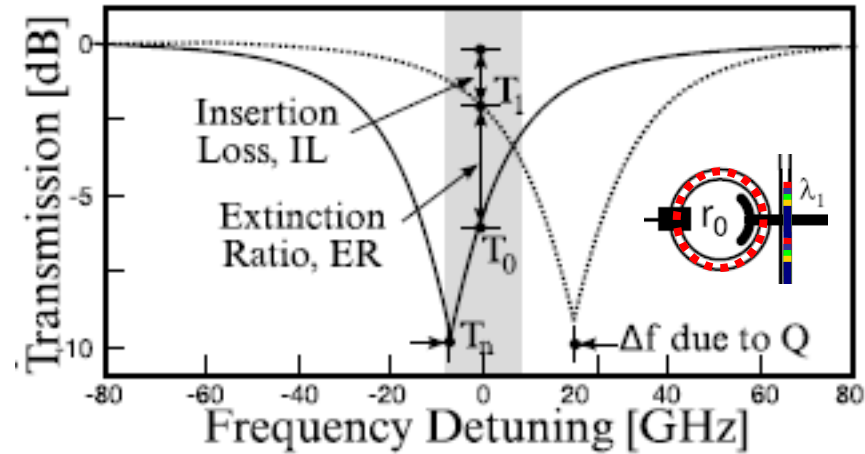
Bulk CMOS Electronics



# Si and polySi waveguide formation



# Integrated photonic interconnects

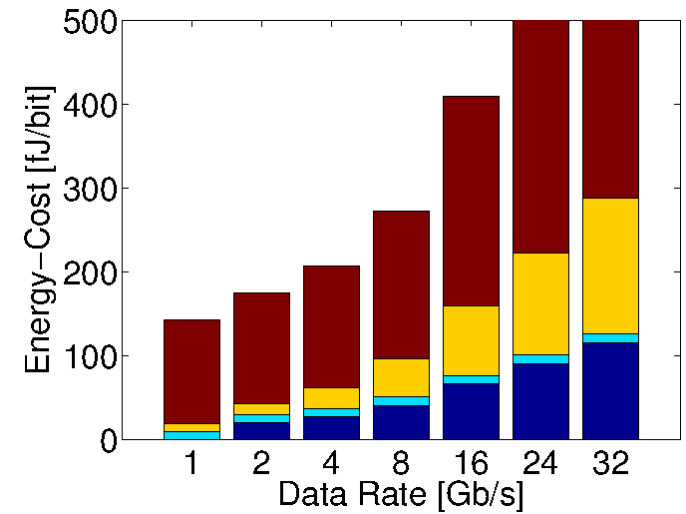
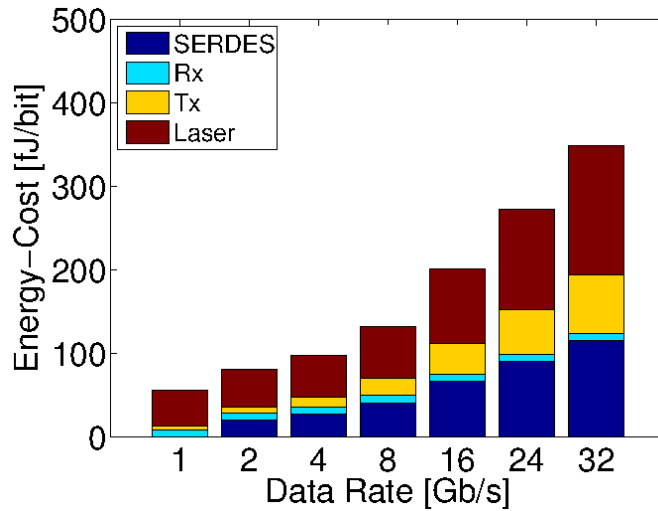


- Each  $\lambda$  carries one bit of data  
 → Bandwidth Density achieved through DWDM  
 → Energy-efficiency achieved through low-loss optical components and tight integration

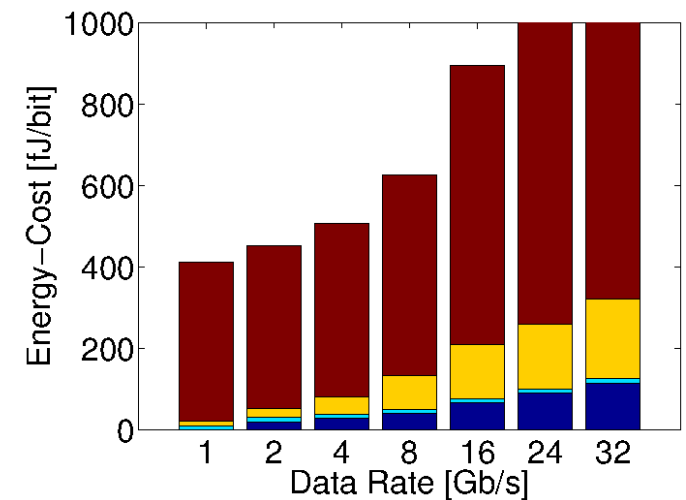
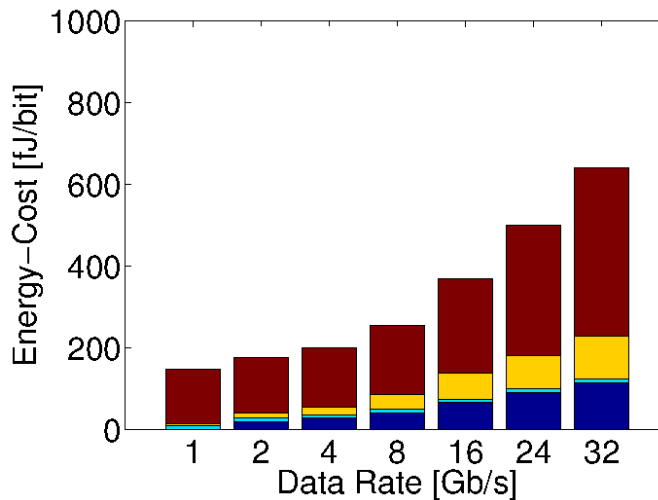
# Single channel link tradeoffs

LOSS

10-dB



15-dB

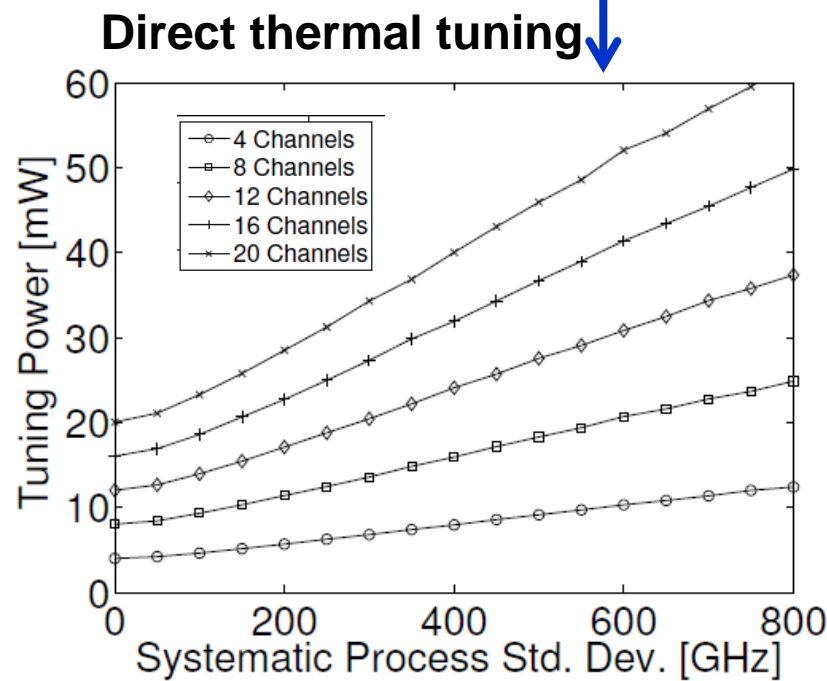
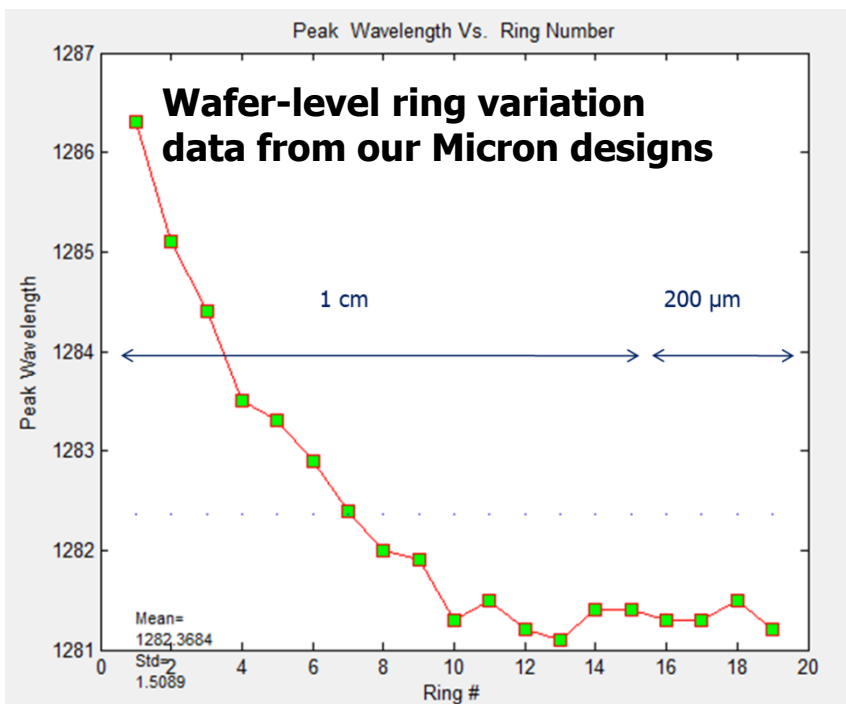
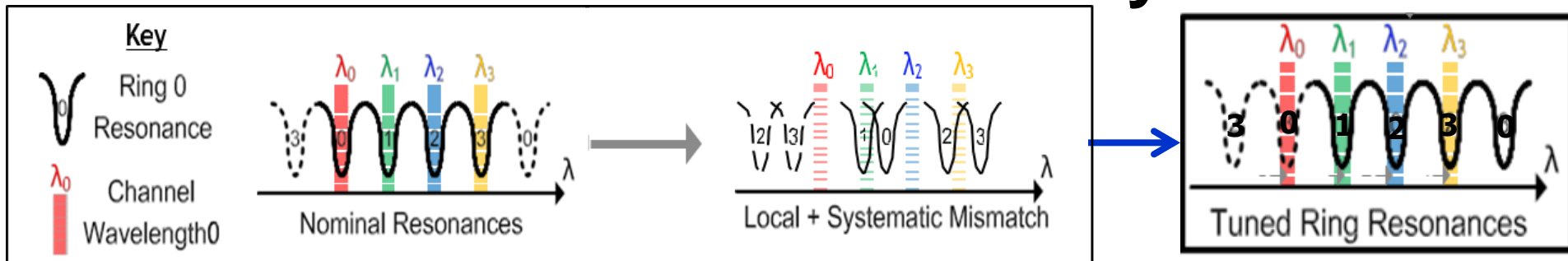


Rx Cap

5-fF

25-fF

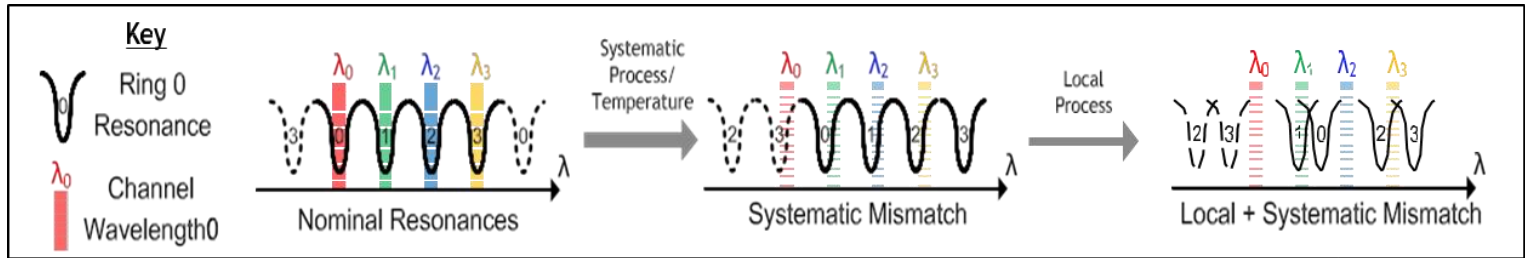
# Resonance sensitivity



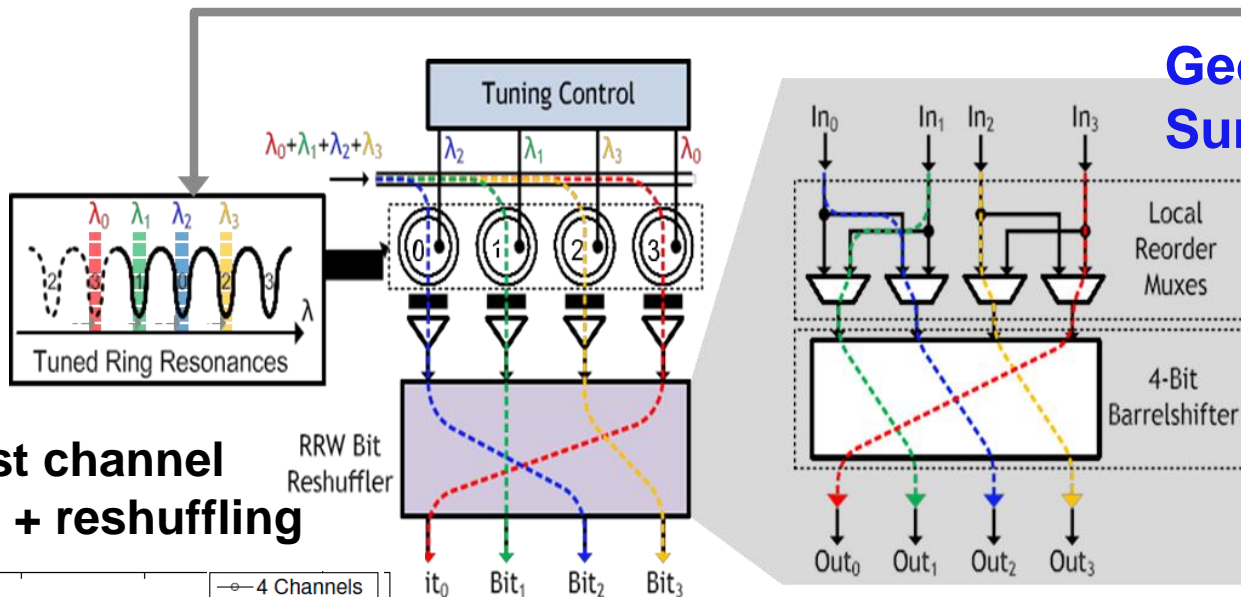
- Process and temperature shift resonances
- Direct thermal tuning cost prohibitive

Georgas CICC 2011, Sun NOCS 2012

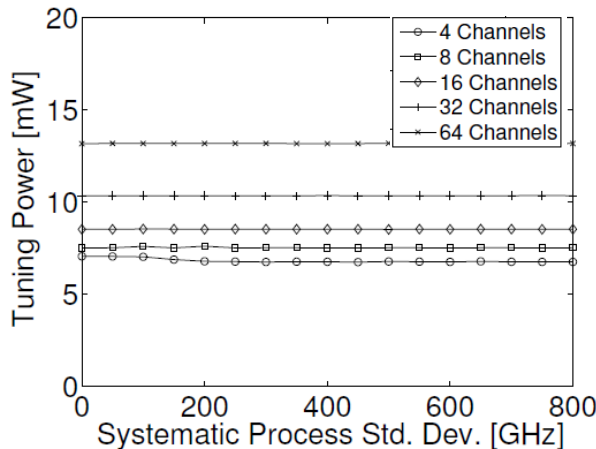
# Smarter wavelength tuning



Georgas CICC 2011,  
Sun NOCS 2012

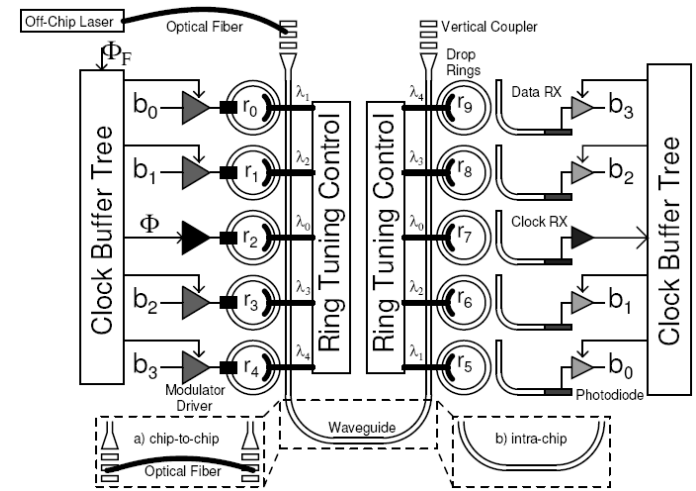
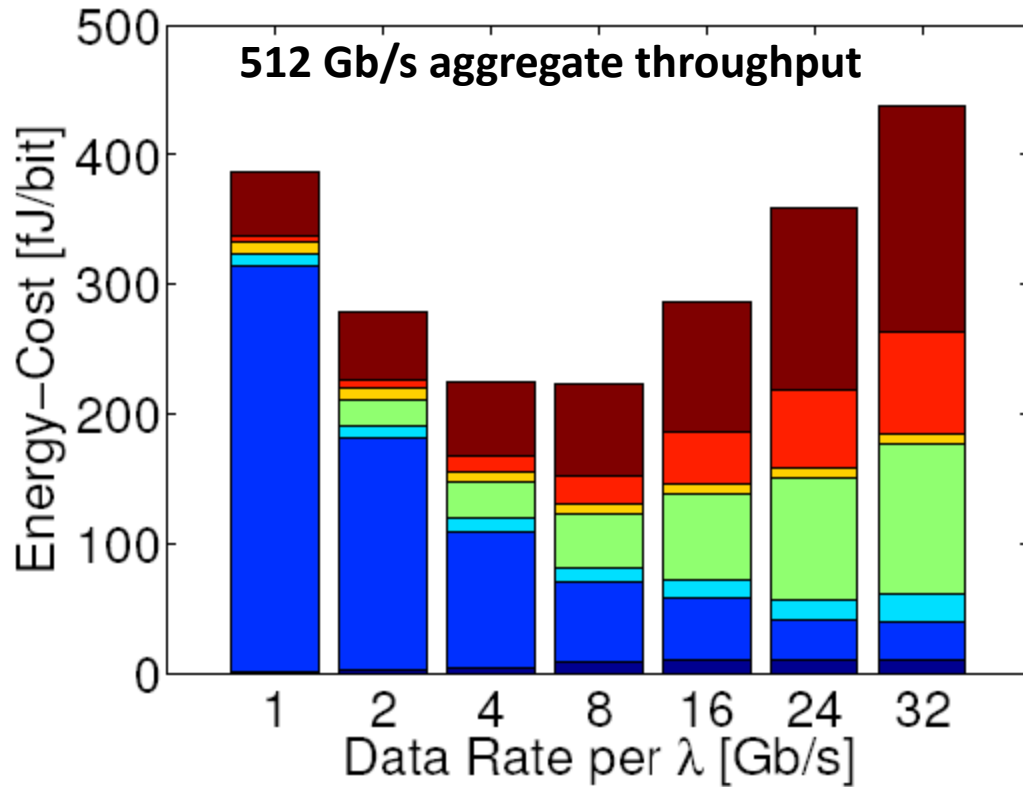


## Nearest channel tuning + reshuffling



- Utilize systematic global mismatch and temperature shifts
- Electrical backend enables dense WDM
  - Helps reduce tuning costs by more than 10x

# Need to optimize carefully

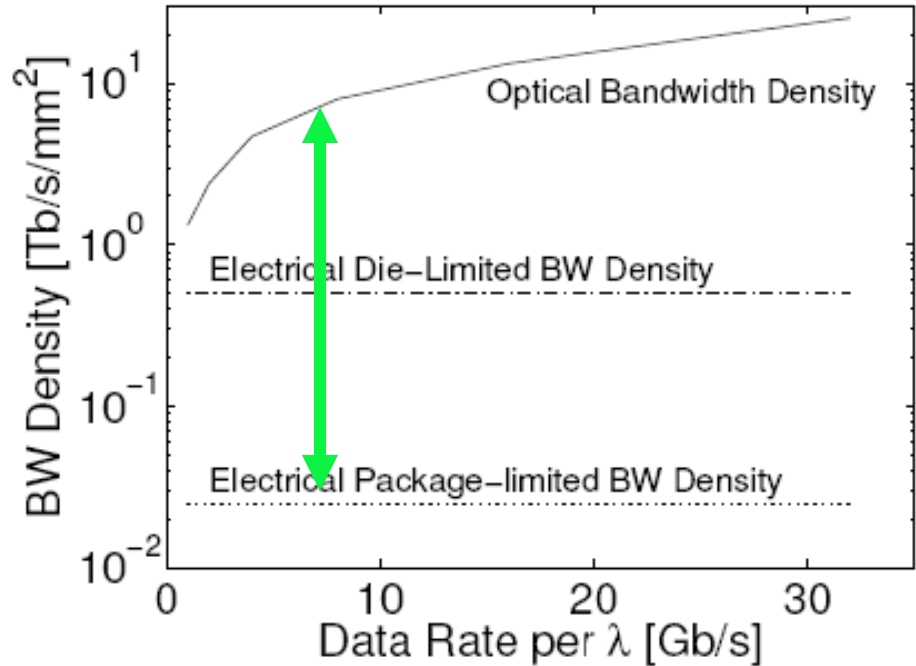
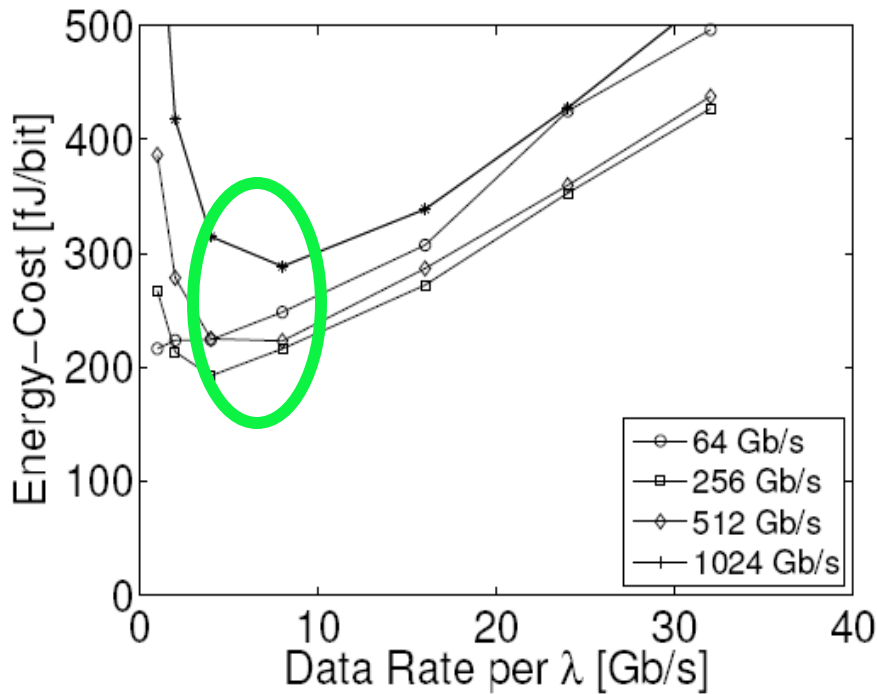


assuming 32nm CMOS

- Laser energy increases with data-rate
  - Limited Rx sensitivity
  - Modulation more expensive -> lower extinction ratio
- Tuning costs decrease with data-rate
- **Moderate data rates most energy-efficient**

**Georgas CICC 2011**

# DWDM link efficiency optimization

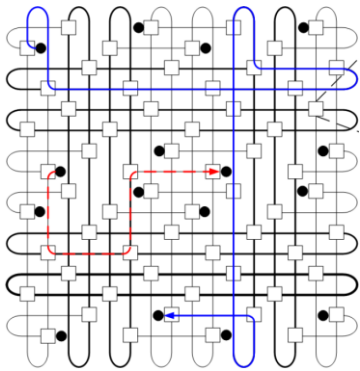


**Optimize for min energy-cost**

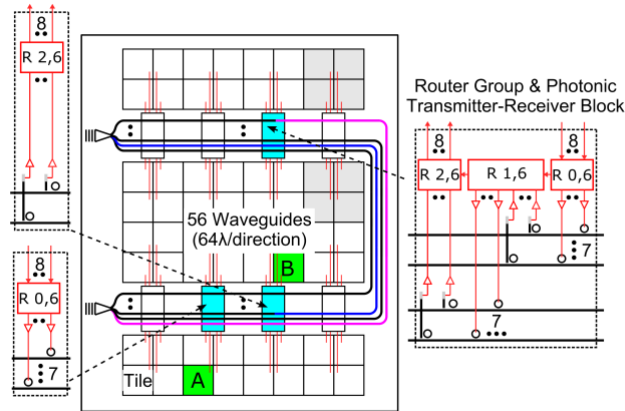
**Bandwidth density dominated by circuit and photonics area  
(not coupler pitch)**

- 10x better than electrical bump limited
- 200x better than electrical package pin limit

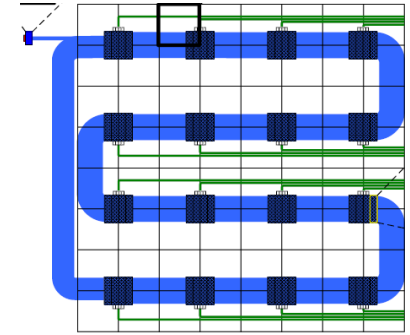
# Many architectural studies show promise



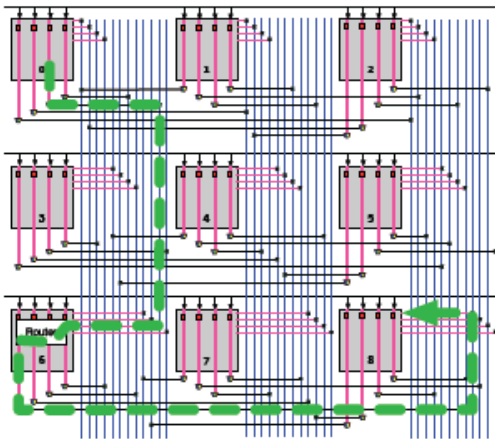
[Shacham'07]  
[Petracca'08]



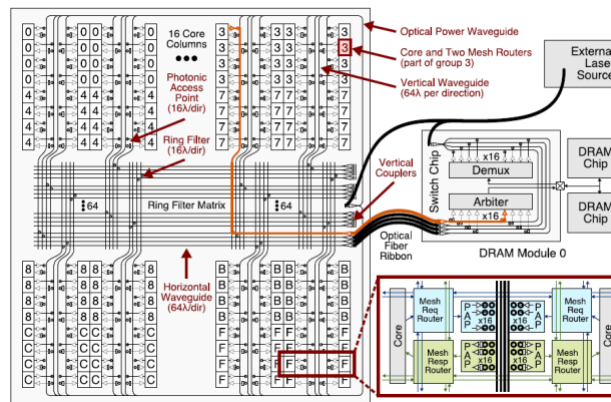
[Joshi'09]  
[Pan'09]



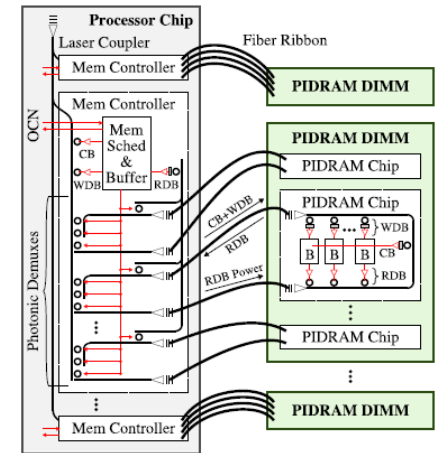
[Vantrease'08]  
[Psota'07]  
[Kirman'06]



[Koka'08-10]



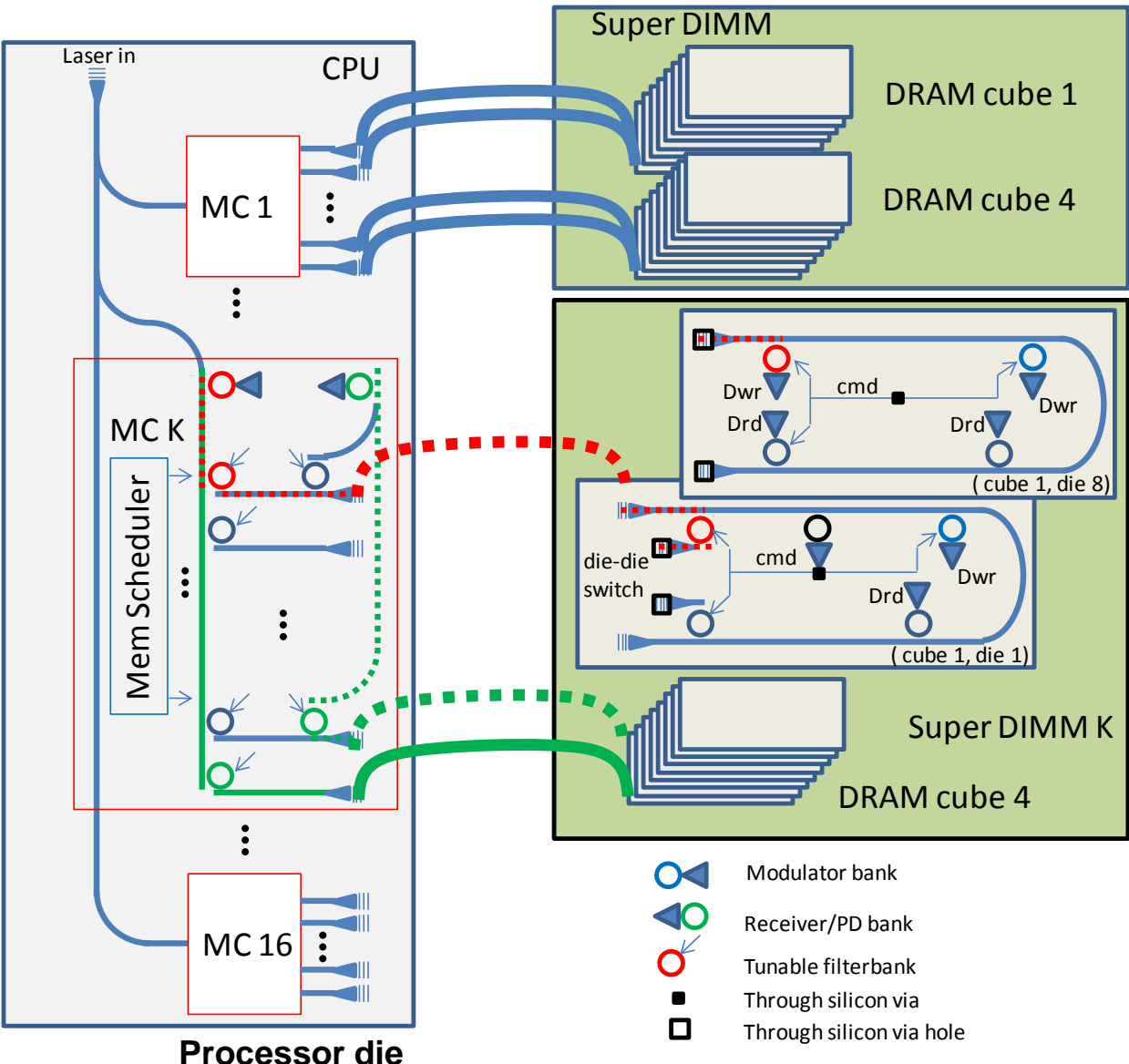
[Batten'08]



[Beamer'10]



# Photonic memory interface – leveraging optical bandwidth density



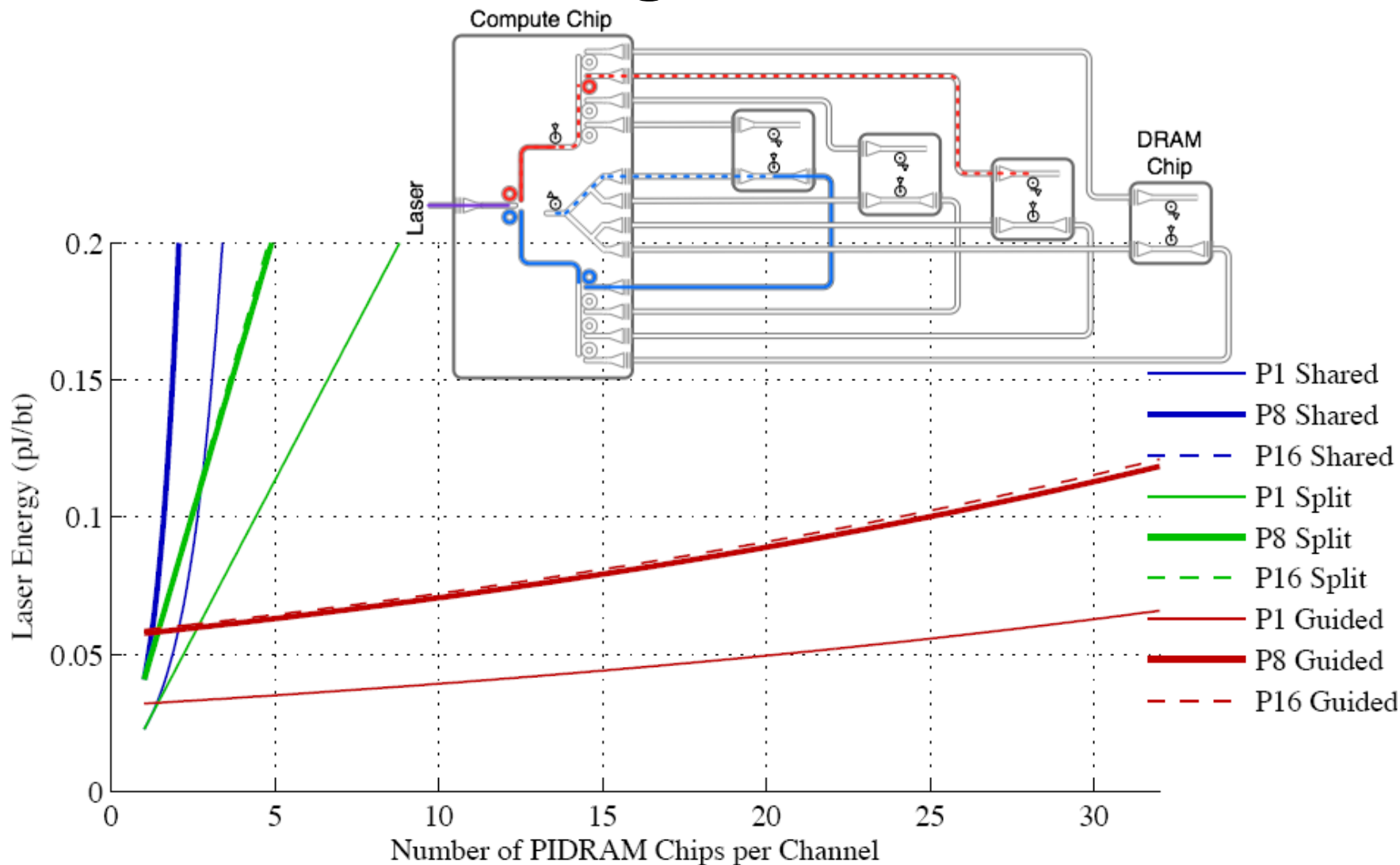
## Important Concepts

- Power/message switching (only to active DRAM chip in DRAM cube/super DIMM)
- Vertical die-to-die coupling (minimizes cabling - 8 dies per DRAM cube)
- Command distributed electrically (broadcast)
- Data photonic (single writer multiple readers)

**Enables energy-efficient throughput and capacity scaling per memory channel**

**Beamer ISCA 2010**

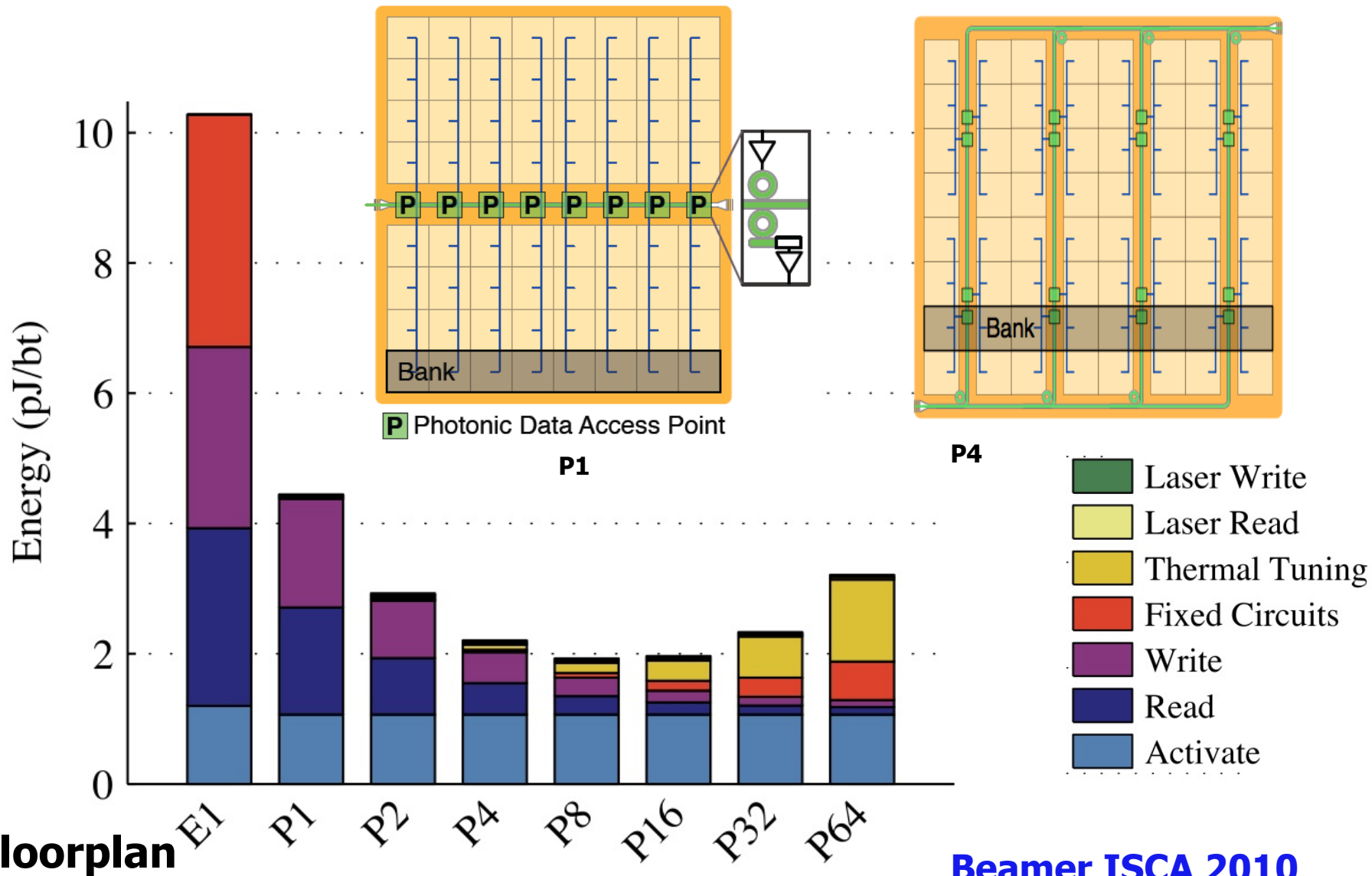
# Laser Power Guiding Effectiveness



**Enables capacity scaling per channel and significant savings in laser energy**

**Beamer ISCA 2010**

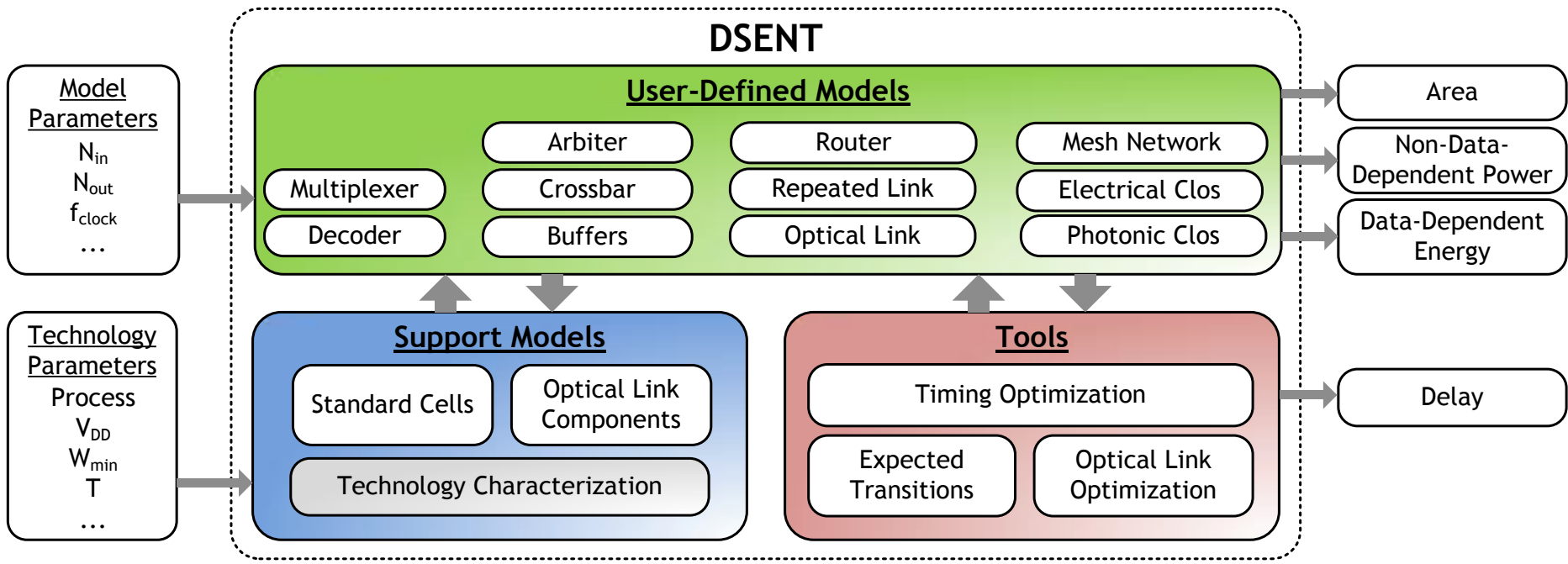
# Optimizing DRAM with photonics



# Design Space Exploration of Networks Tool

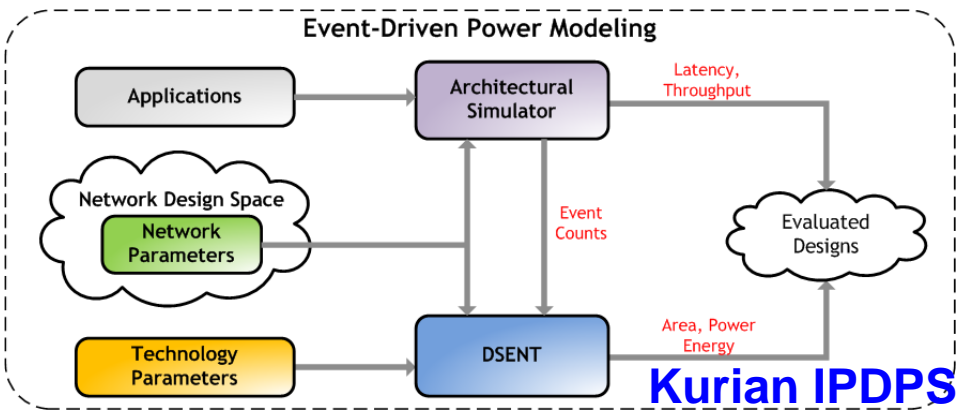
DSENT – A Tool Connecting Emerging Photonics with Electronics for Opto-Electronic Networks Modeling

Chen NOCS 2012



Available for download at:

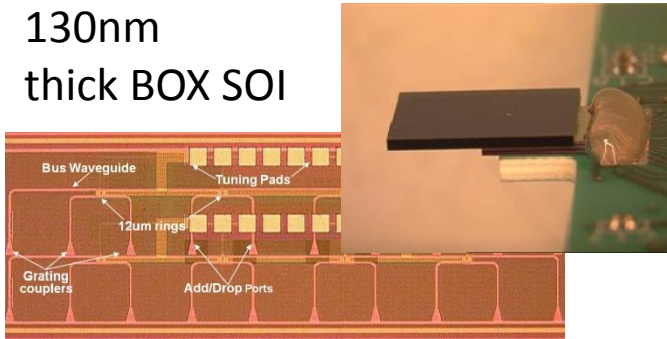
<https://sites.google.com/site/mitdsent/>



Kurian IPDPS 2012

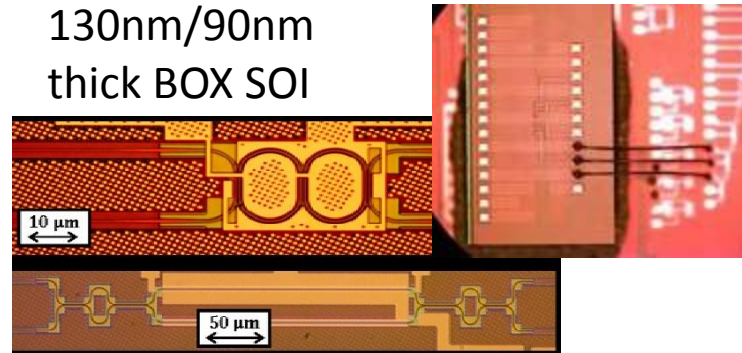
# Significant integration activity, but hybrid and older processes ...

130nm  
thick BOX SOI

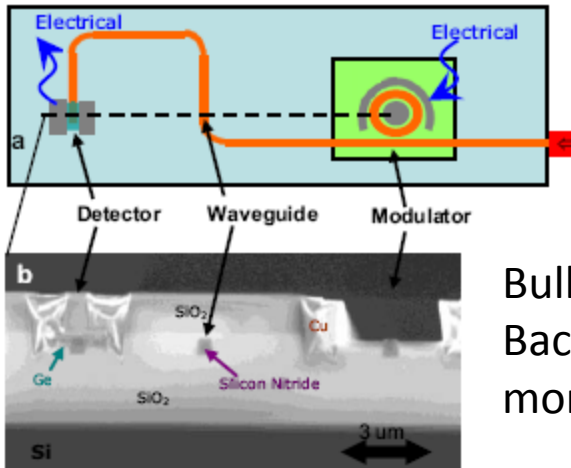


[Luxtera/Oracle/Kotura]

130nm/90nm  
thick BOX SOI

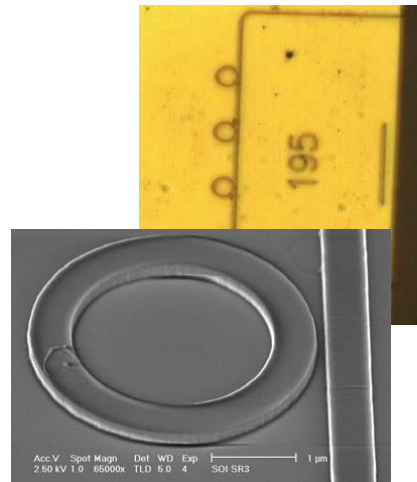


[IBM]



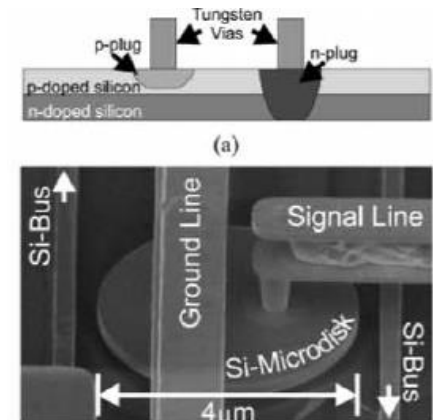
Bulk CMOS  
Backend  
monolithic

[Intel]



[HP]

[Many schools]

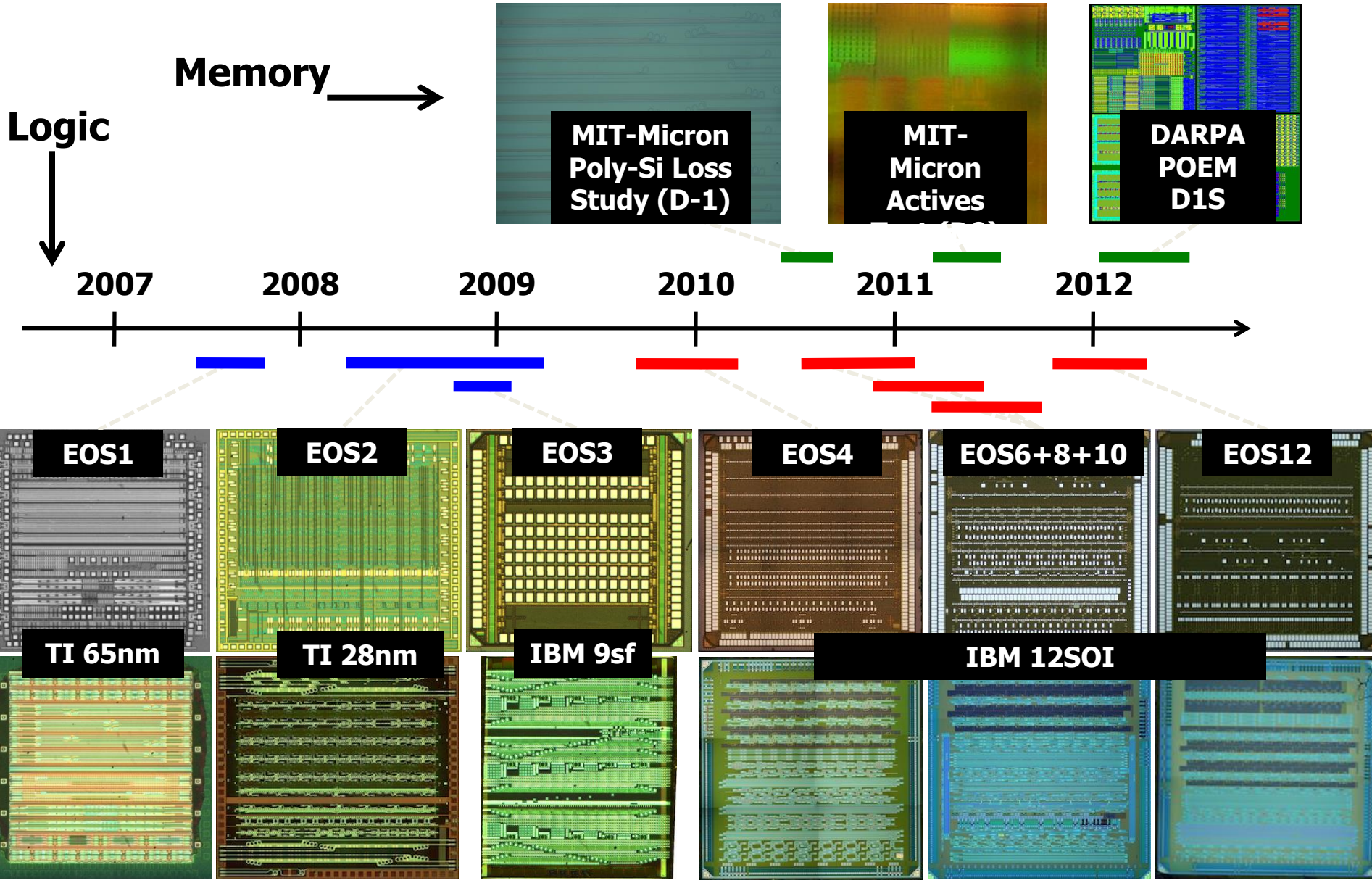


[Watts/Sandia/MIT]

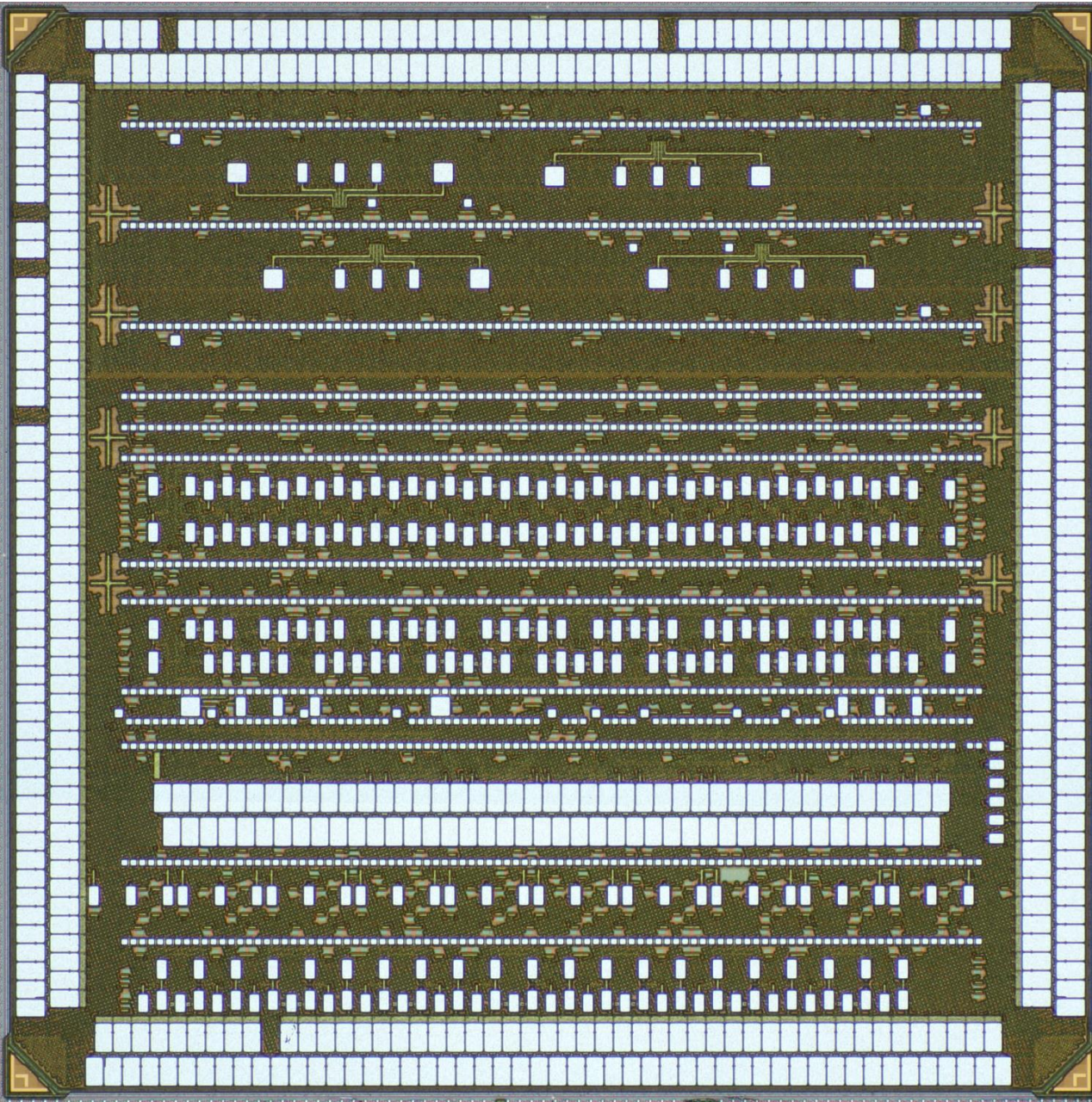
[Lipson/Cornell]

[Kimerling/MIT]

# Our work: Si Electronic-Photonic Integration Timeline



# EOS Platform: EOS8 fabricated in IBM12SOI



Orcutt et al,  
Optics Express, 2012

3 x 3 mm die

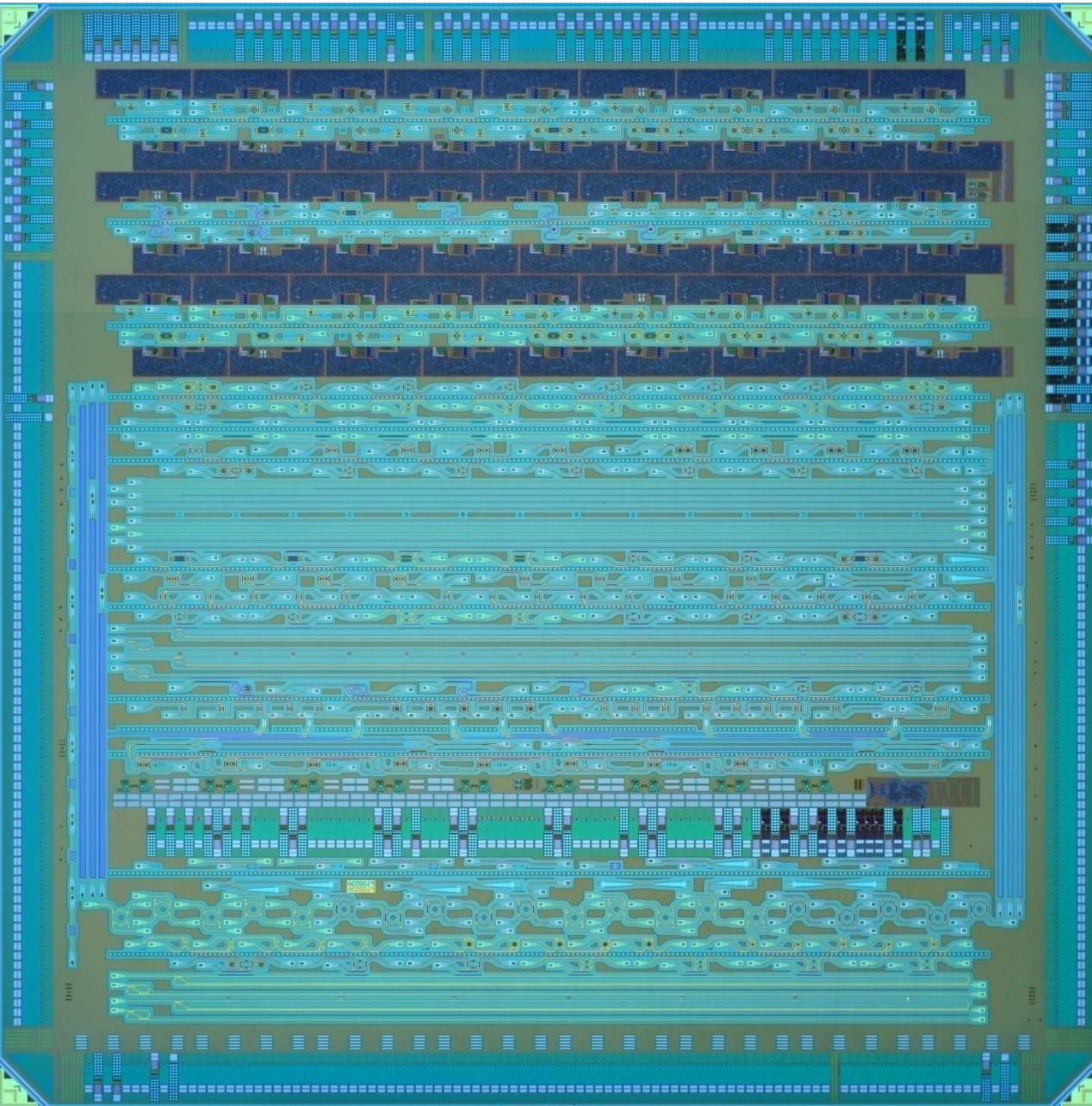
45nm Thin Box SOI  
Technology  
(used for Power 7 and  
Cell processors)

3M Transistors

400 Pads

ARM Standard Cells  
and  
custom link circuits

# EOS8 performance summary



**Fiber-to-chip grating couplers with 3.5 dB insertion loss**

**Waveguides under 4dB/cm propagation loss**

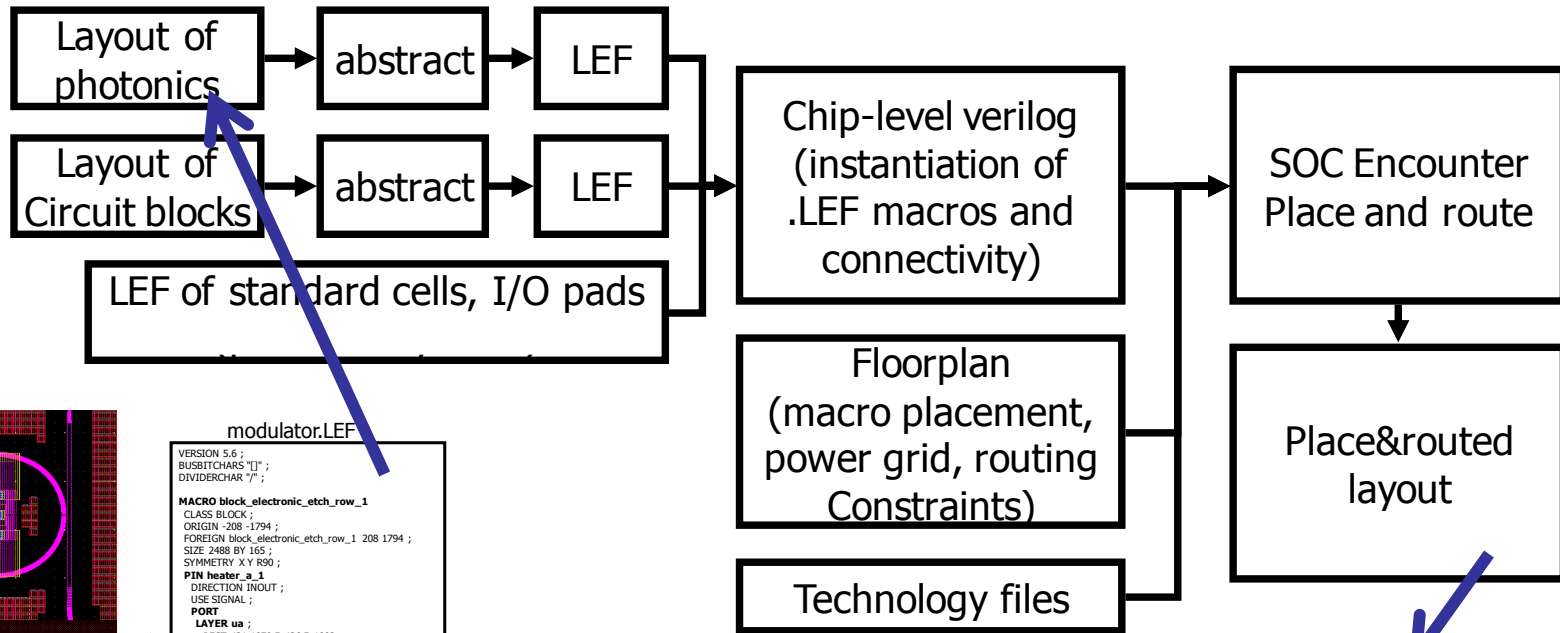
**10 dB extinction optical modulators**

**8 channel wavelength division multiplexing filter bank with <math>< -20\text{ dB}</math> cross talk**

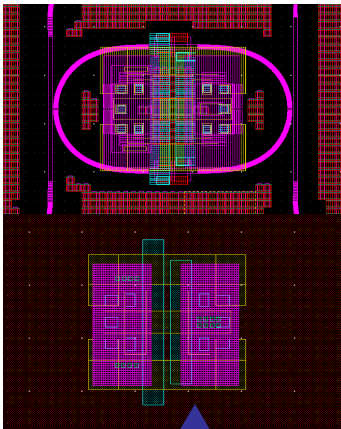
**All integrated with electronic circuits**



# Integration of photonics into VLSI tools



layout



```

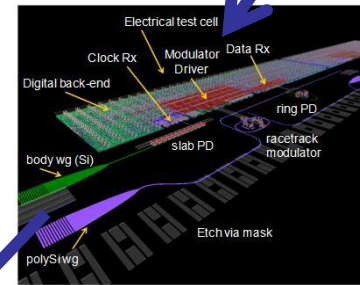
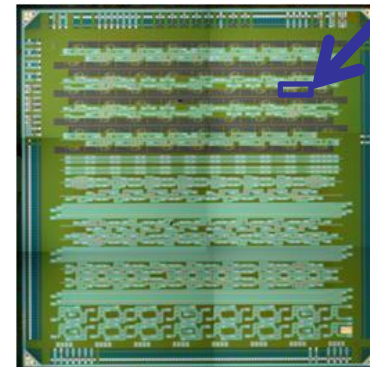
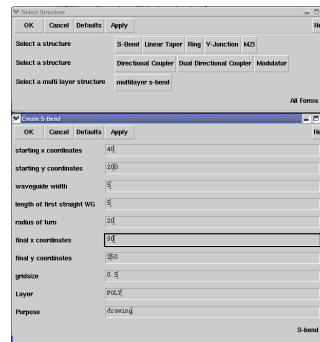
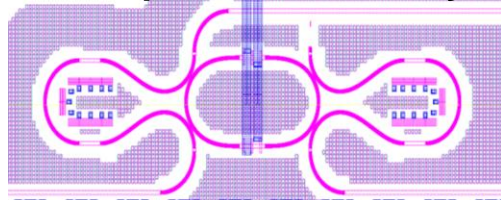
modulator.LEF
VERSION 5.6 ;
BUSBITCHARS "1";
DIVIDERCHAR "?";

MACRO block_electronic_etch_row_1
CLASS BLOCK;
ORIGIN -208 -1794 ;
FOREIGN block_electronic_etch_row_1 208 1794 ;
SIZE 2488 BY 165 ;
SYMMETRY X Y R90 ;
PIN heater_a_1
DIRECTION INOUT ;
USE SIGNAL ;
PORT
LAYER ua ;
RECT 431 1870.5 436.5 1882 ;
END
END heater_a_1
...
OBS
LAYER m1 ;
RECT 208 1794 2696 1959 ;
...
END
END block_electronic_etch_row_1
END LIBRARY
  
```

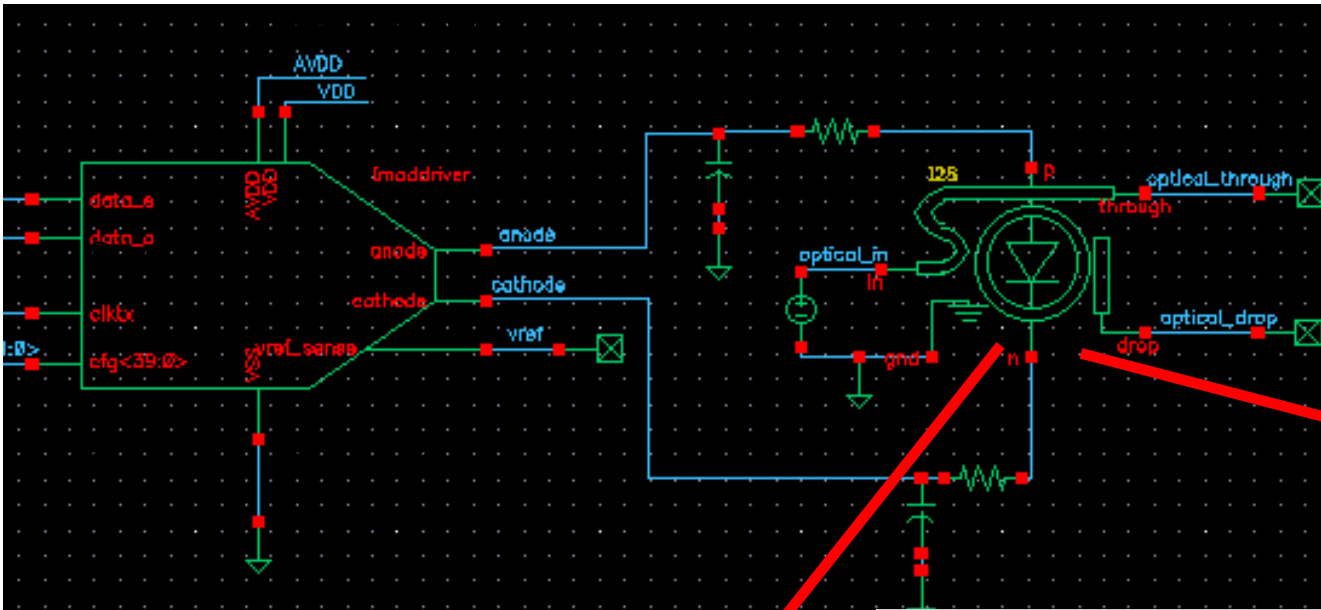
Photonic device  
p-cell

abstract

custom photonics-friendly auto-fill



# Circuit/Device Co-Simulation: VerilogA



```

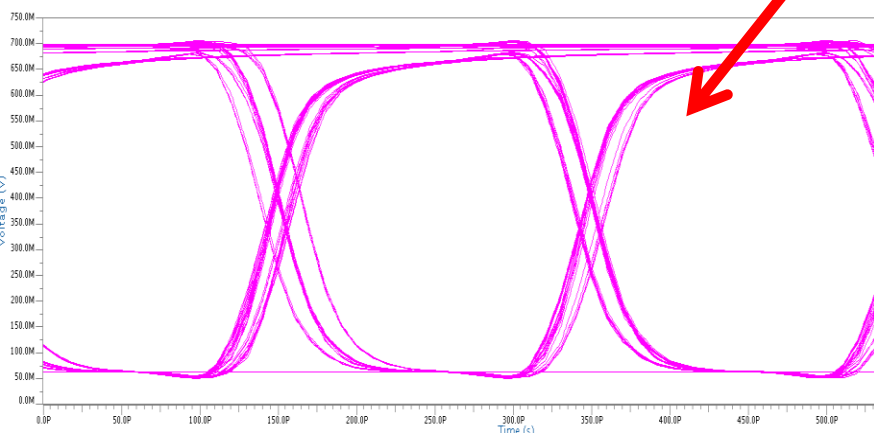
Session Edit View Bookmarks Settings Help

VerilogA for d1_moddriver, modulator_ridge, veriloga

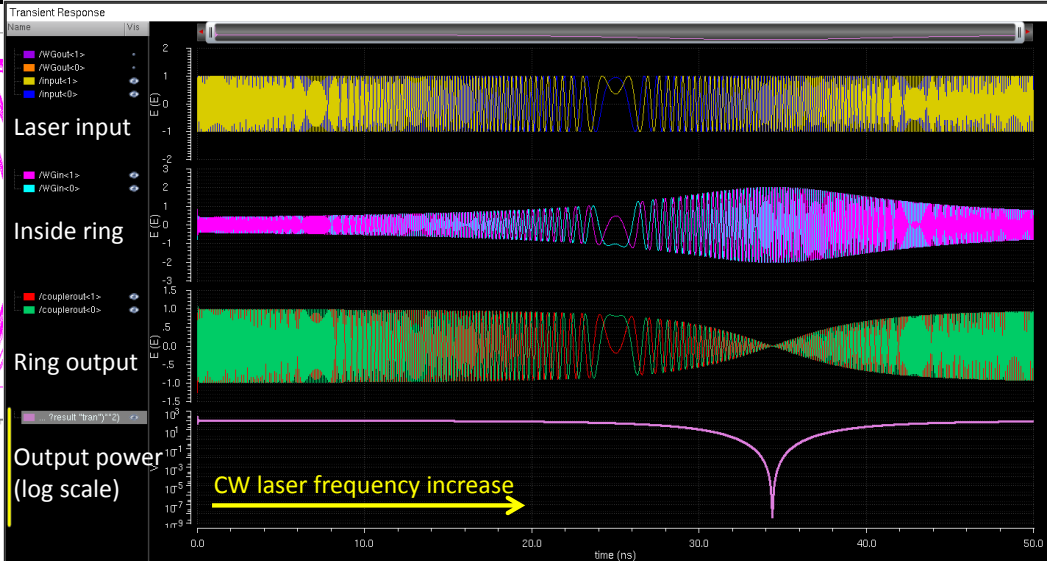
#include "disciplines.vams"

/*
Changelog:
22 Dec Updates from Milos & Jeff:
*/
module modulator_ridge(p, n, gnd, in, through, drop)
// -----
// DEFINE PORTS
// -----
    inout p, n, gnd;
    input in;
    output through, drop;
    electrical p, n, gnd, in, through, drop;
    branch (p,n) res, cap;

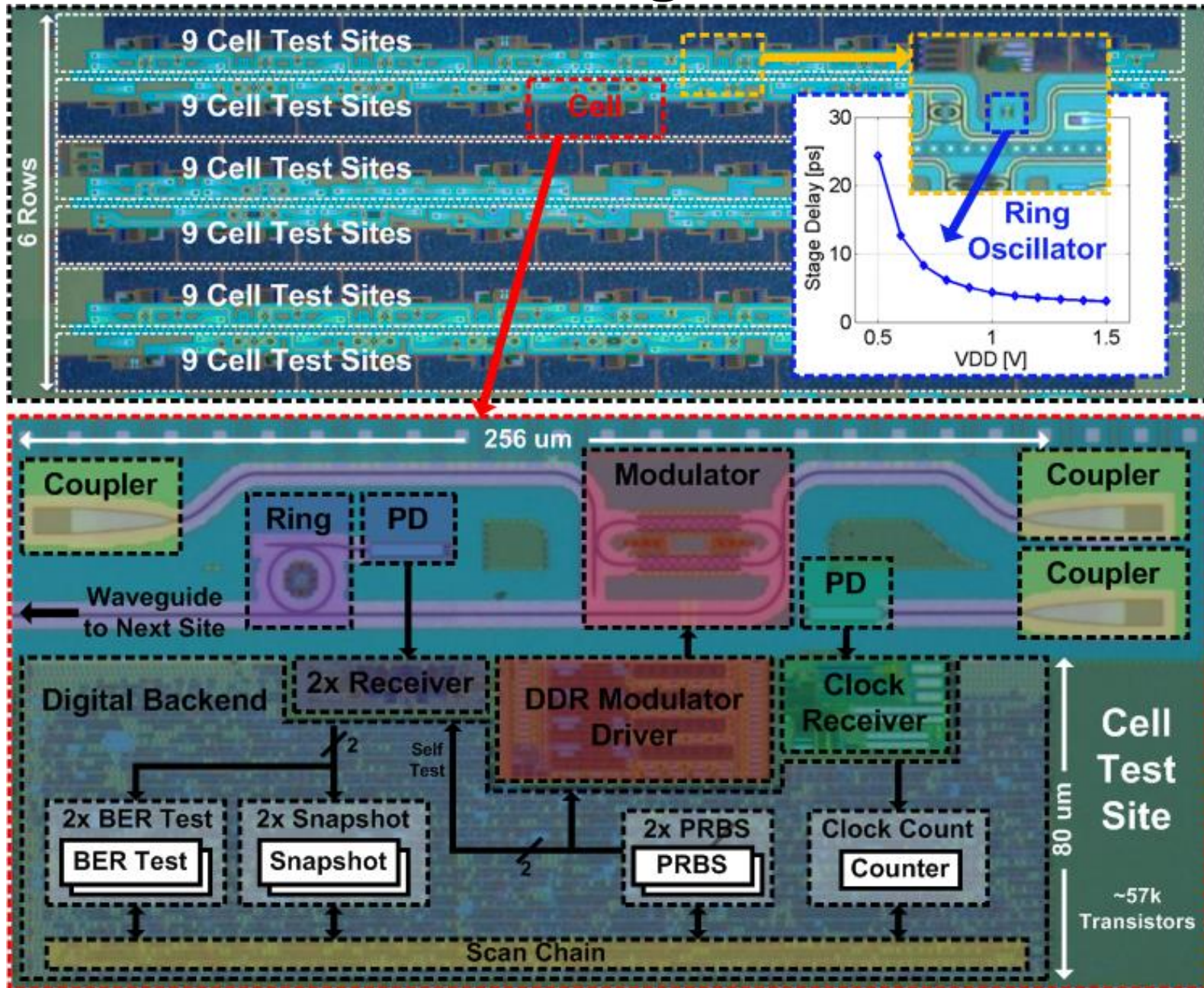
// -----
// OPTICAL PARAMETERS
// -----
// Physical Constants
    parameter real pi      = 3.1415926536; // Pi [unitless]
    parameter real k       = 1.38e-23;   // Boltzmann const
    parameter real T       = 300;        // Temperature [K]
    parameter real q       = 1.6e-19;    // Charge of elect
    parameter real eo      = 8.85e-12;   // Permittivity of
    parameter real es      = 12;         // Relative permit
    parameter real c       = 3e8;        // Speed of light
    parameter real nf      = 3e-27;     // Refractive index
  
```



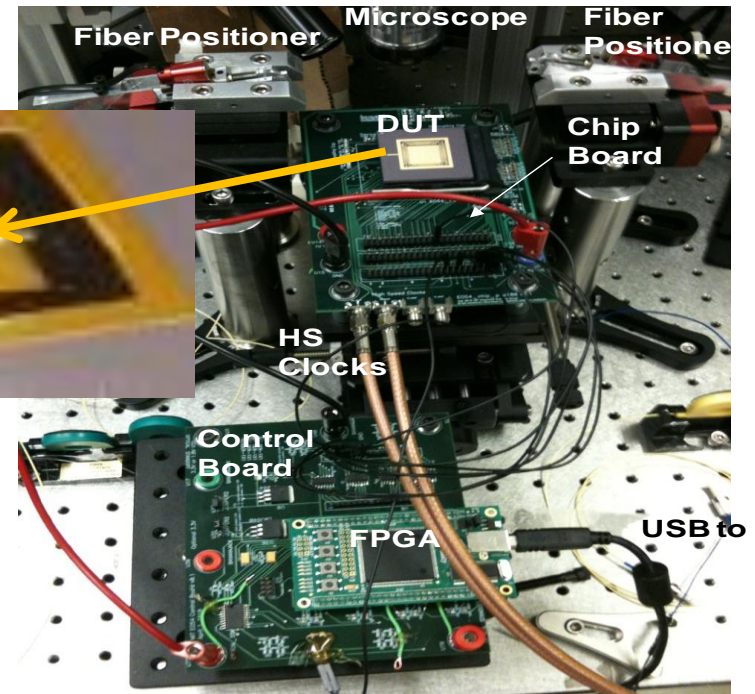
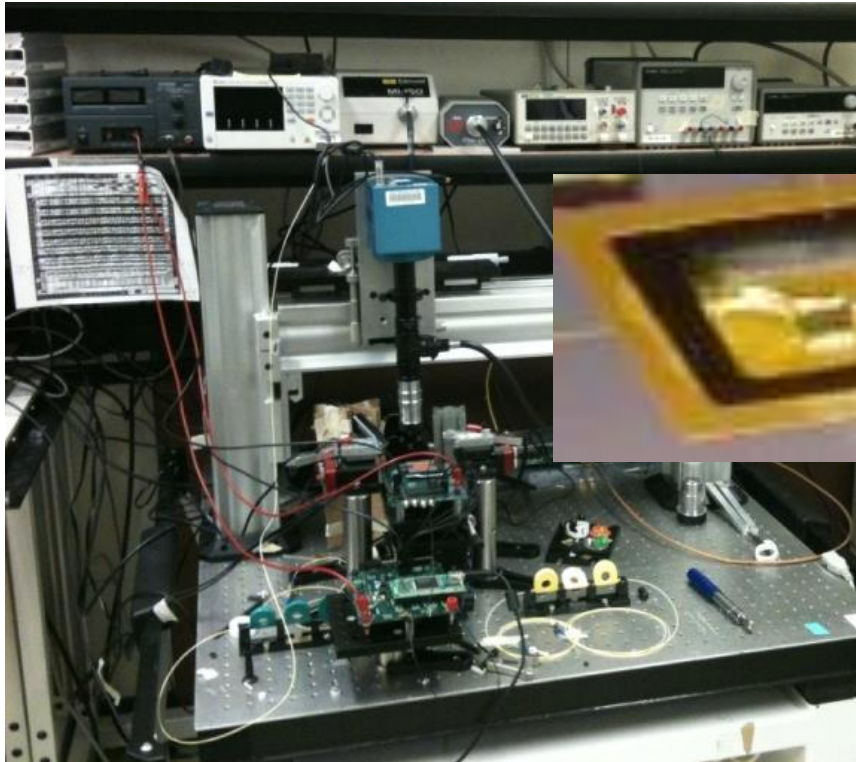
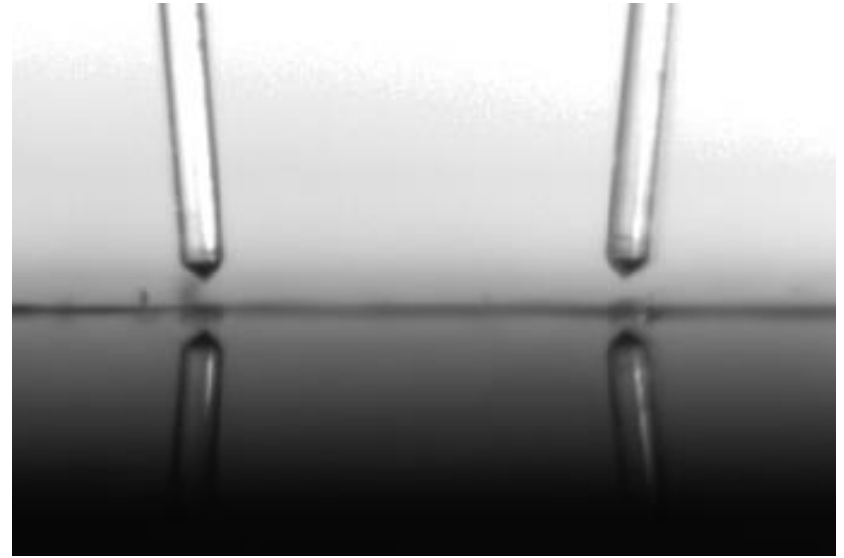
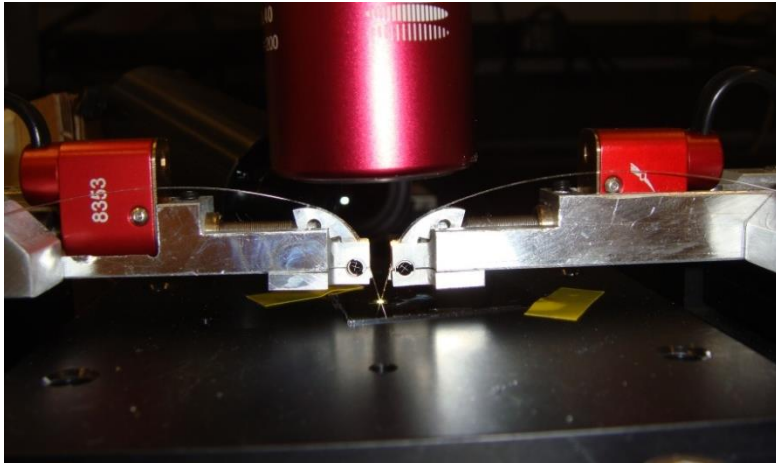
Optical Eye Diagram



# Platform Organization

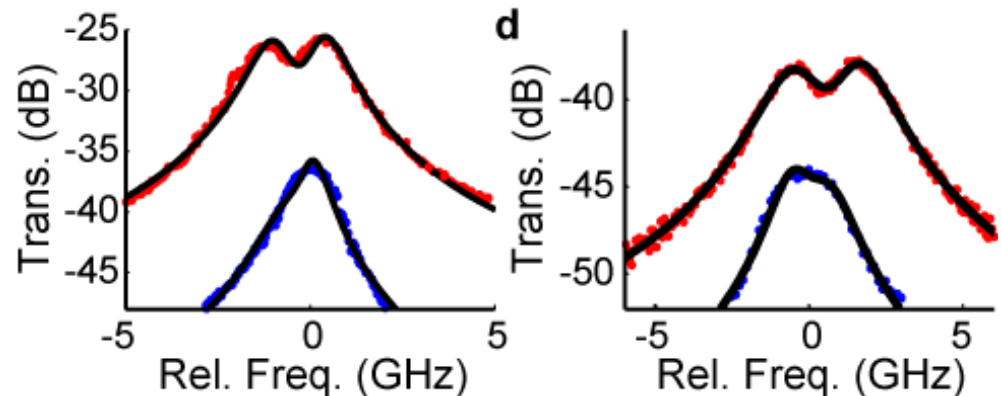
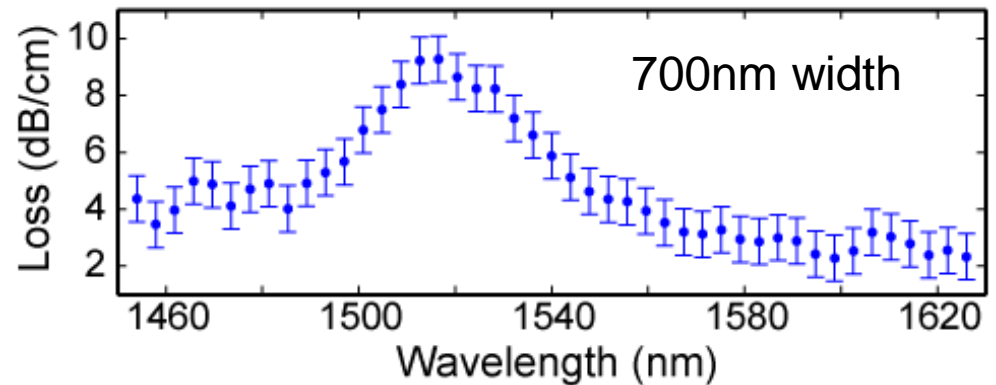
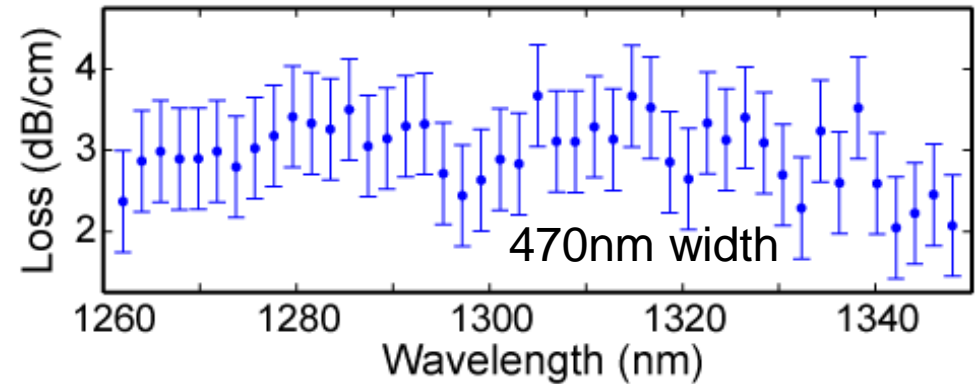


# Chips fully packaged

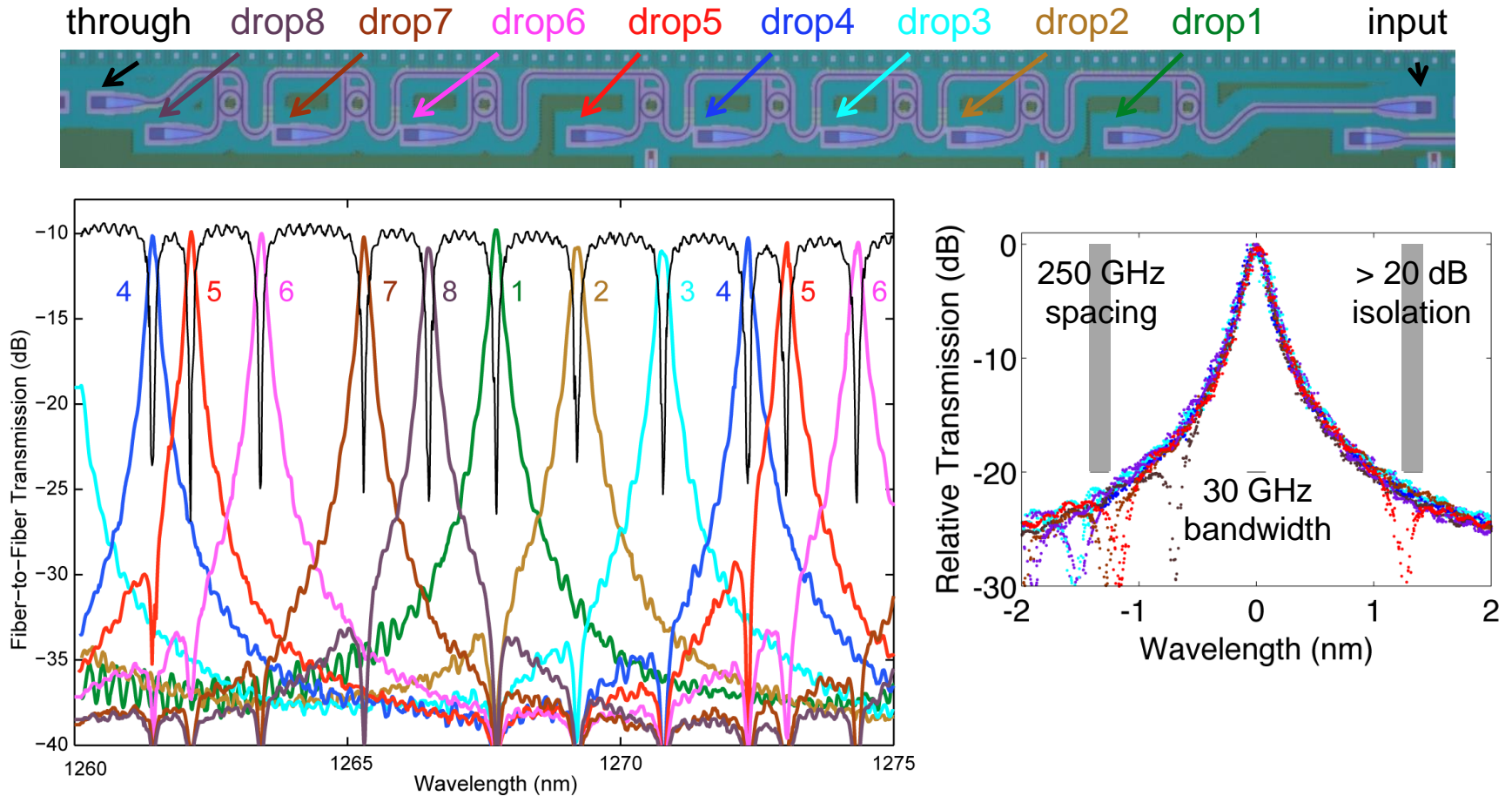


# Best waveguide losses ever reported in a sub-100nm production CMOS line

- Body-Si waveguides
  - 3-4dB/cm loss
- Poly waveguides
  - 50dB/cm loss
- Body-Si ring Q factor
  - 227k @ 1280nm
  - 112k @ 1550nm

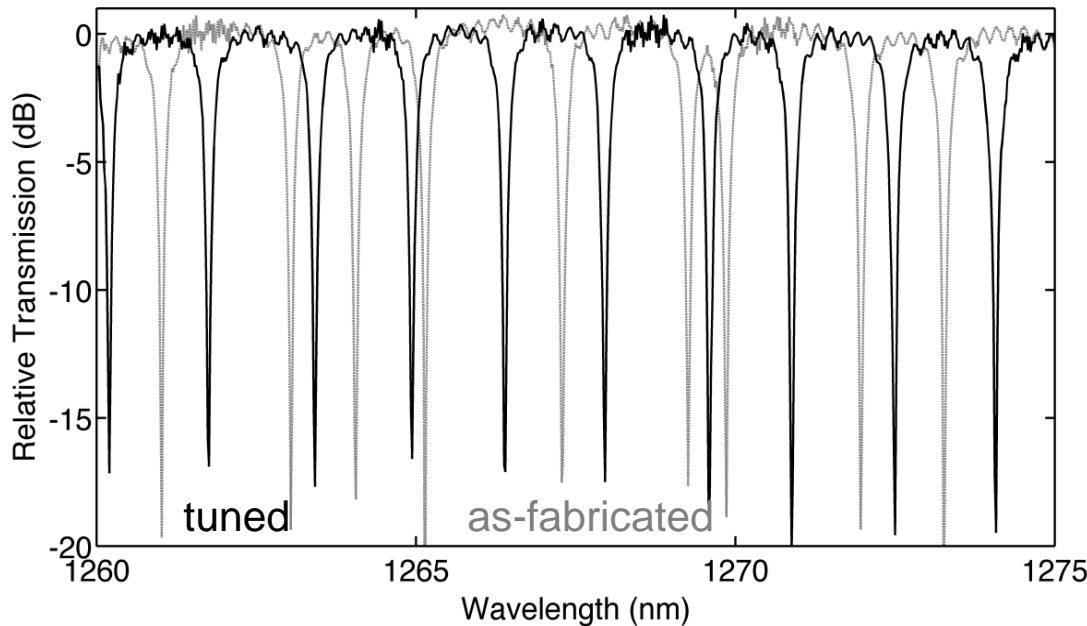
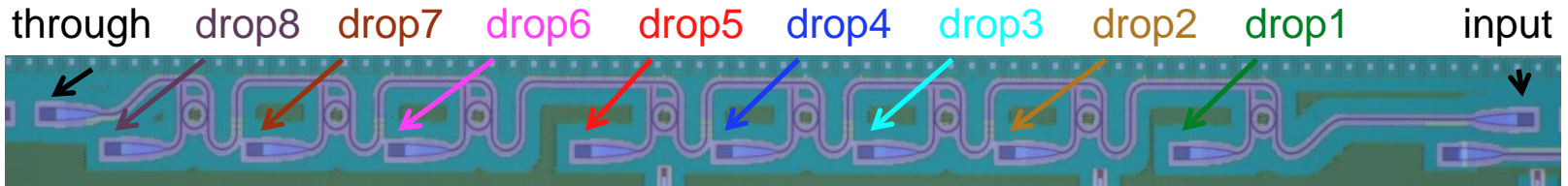


# Exceptional dimensional control in 45nm node

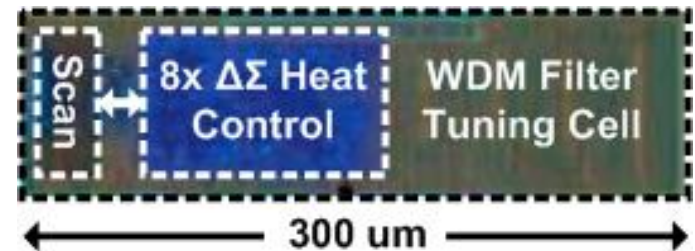


- 8-wavelength filterbank results
  - Filter channels fabricated in order
  - Less than 1nm variation
- Excellent channel isolation (>20dB at 250GHz spacing)

# Integrated thermal tuning circuits

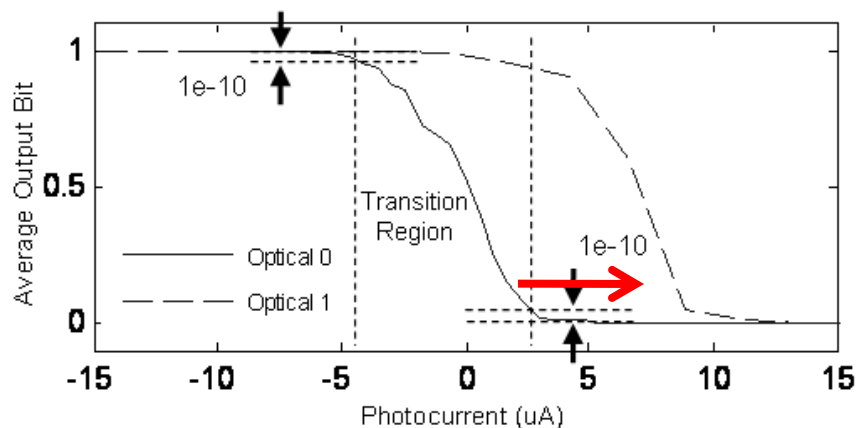
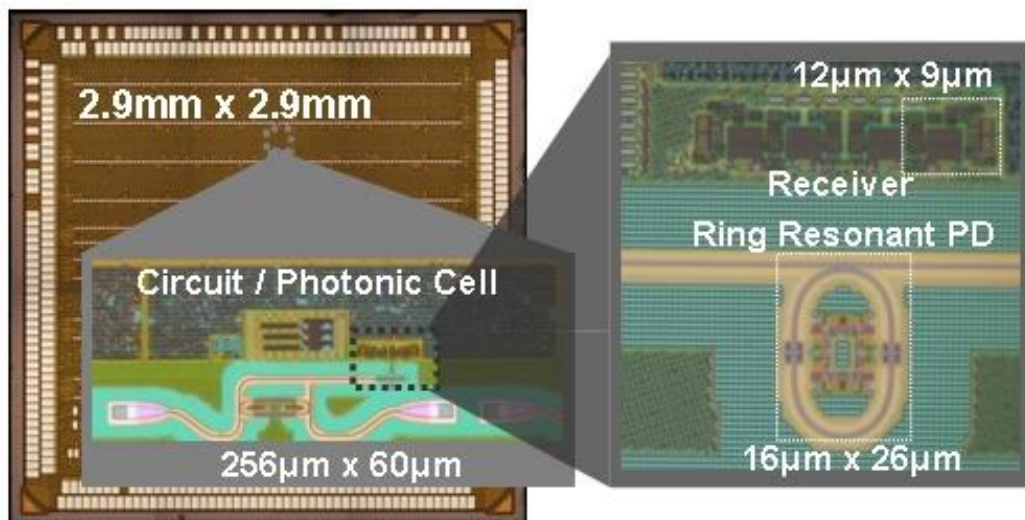
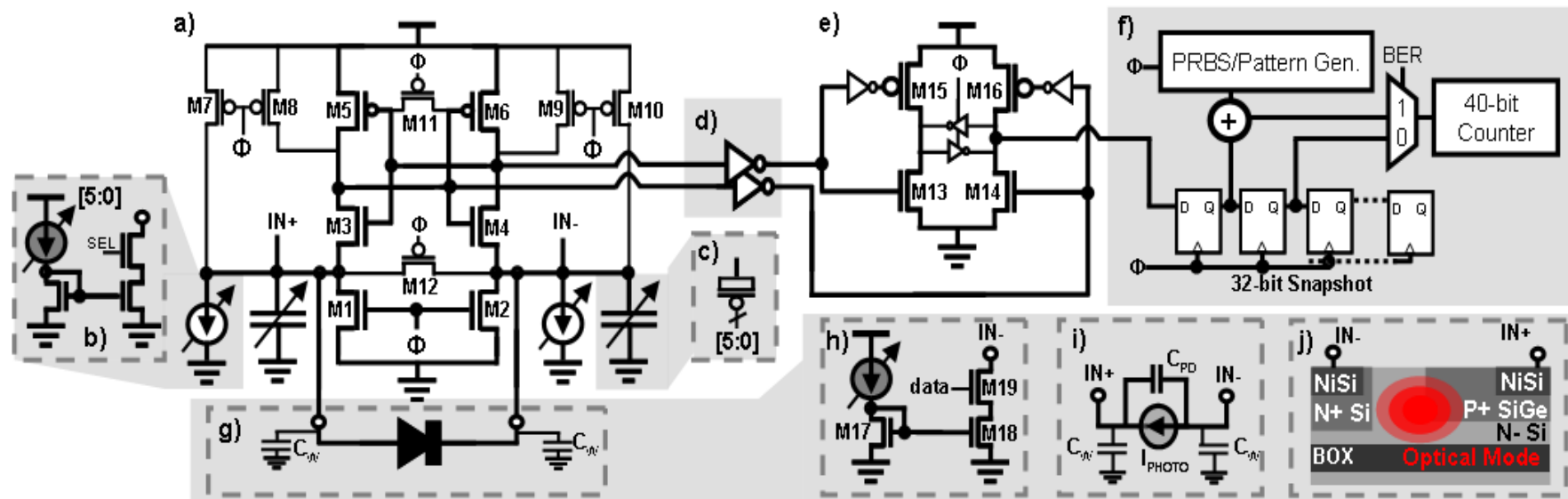


## integrated digital PWM heater controller



- 10mW required to retune all 8 rings
  - Negligible overhead of tuning circuits (thermal BW < 500kHz)
  - Tuning efficiency 130uW/K (32.4mW/2 $\pi$ ) – fully substrate released chips

# Low-power current-sensing optical receiver

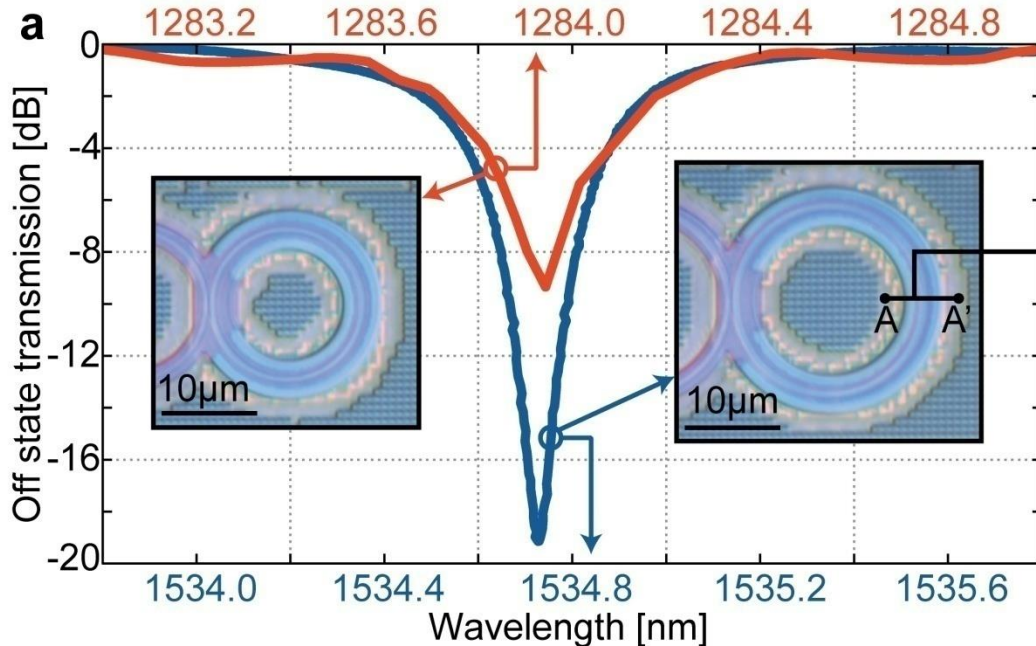
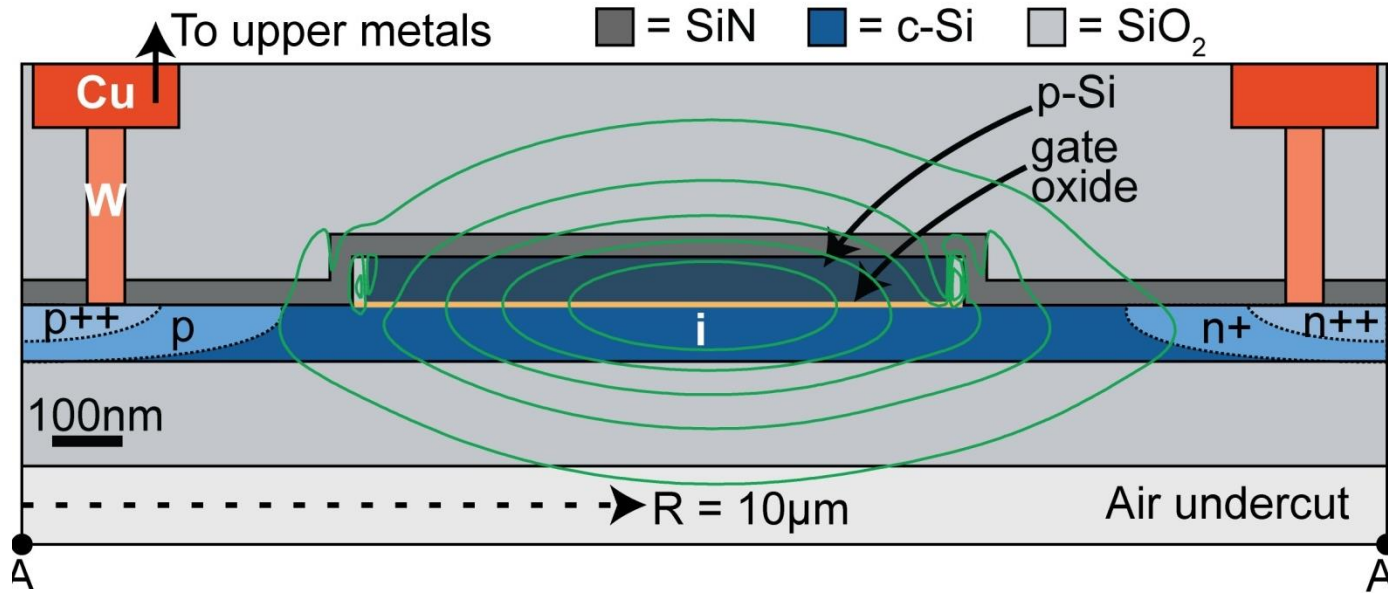


Receiver detects photo current 50fJ/b, uA sensitivities, 3-5Gb/s



# Optical modulator design

Shainline, Popovic



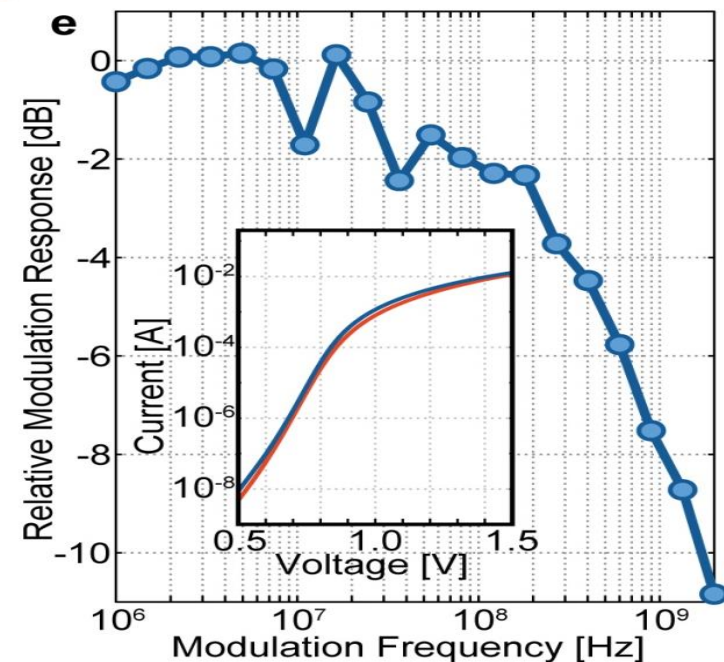
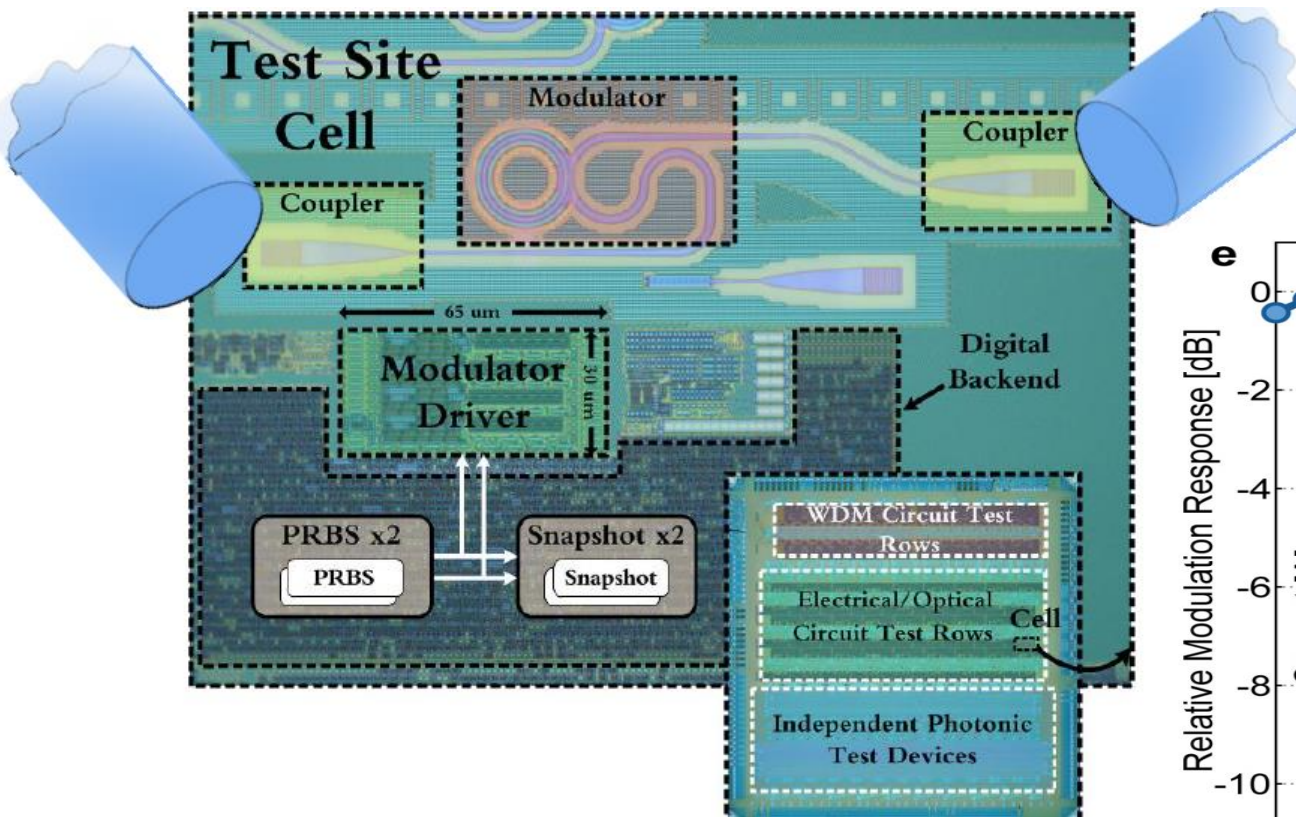
Carrier-injection device  
at 1550nm

- Extinction ratio 19dB
- 45GHz 3dB optical bw

at 1280nm

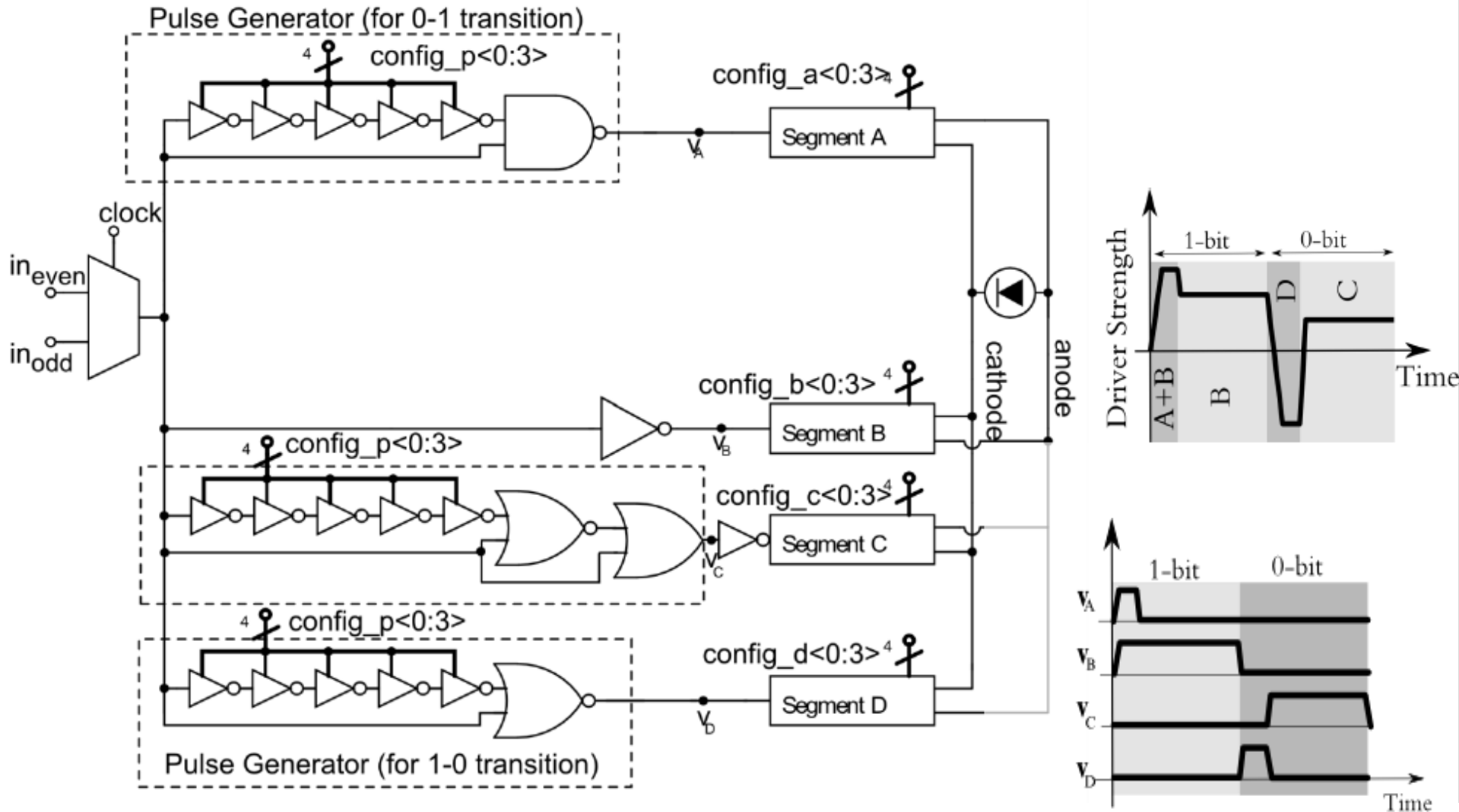
- Extinction ratio 9dB
- 60GHz 3dB optical bw

# Optical modulator – electrical tests



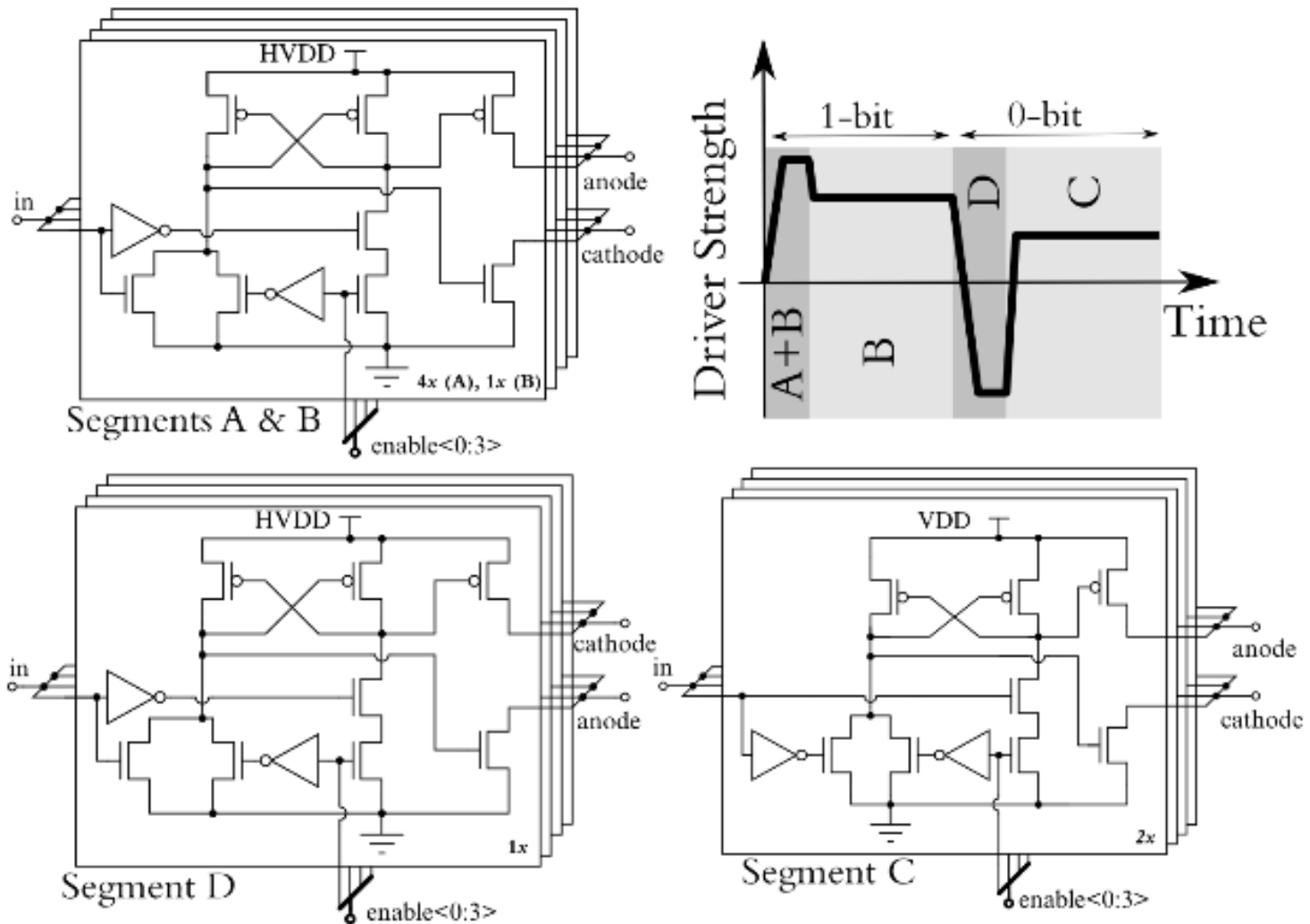
- Carrier-lifetime 2-3ns  $\rightarrow$  **200MHz electrical bandwidth**
  - Diffusion time constant affected by
    - Recombination time
    - Drift conditions

# Modulator driver sub-bit pre-emphasis



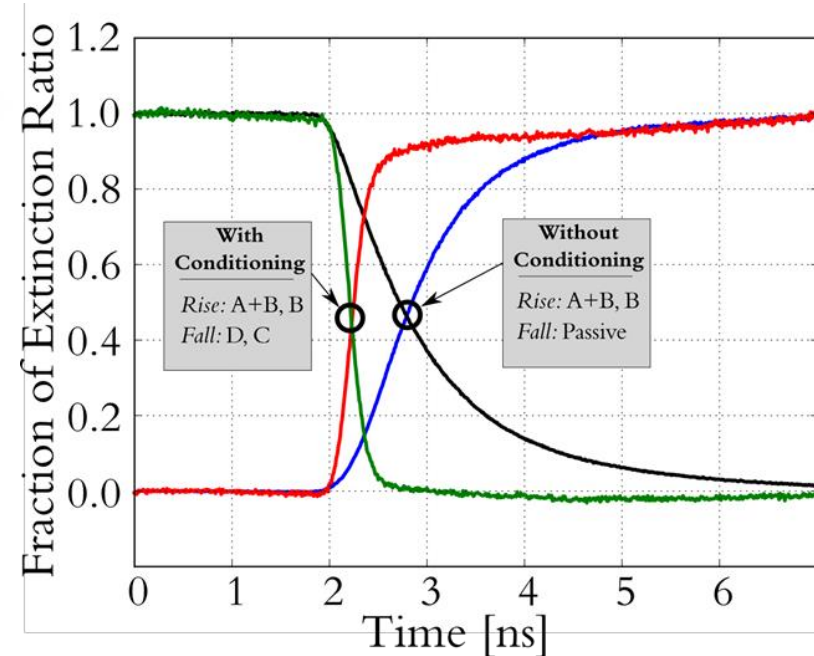
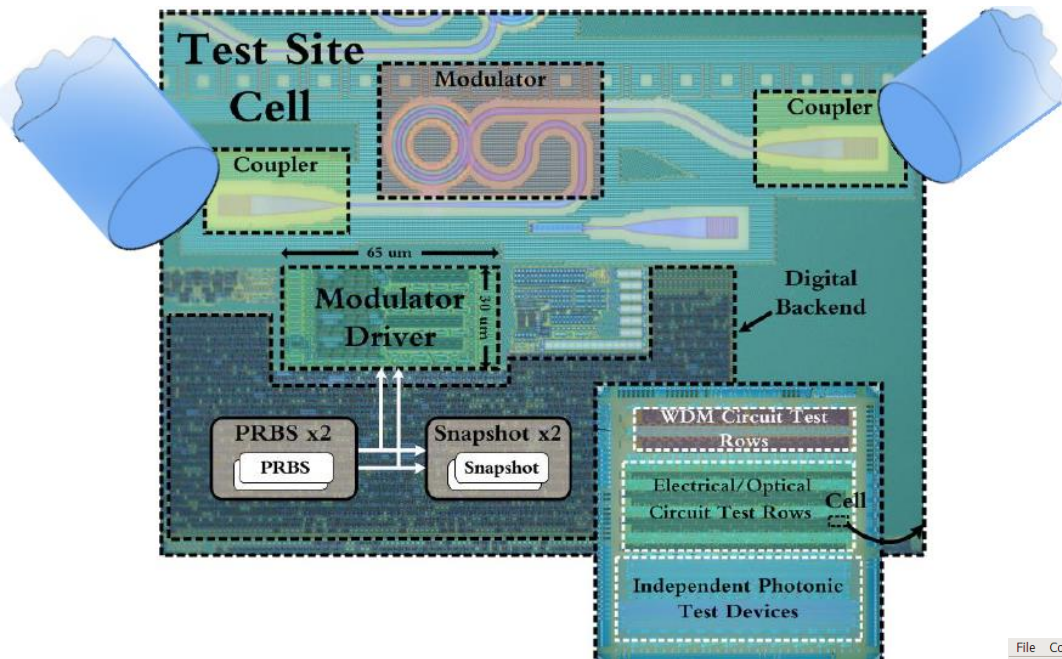
- Partial forward bias at 0-bit key to fast operation

# Modulator driver heads

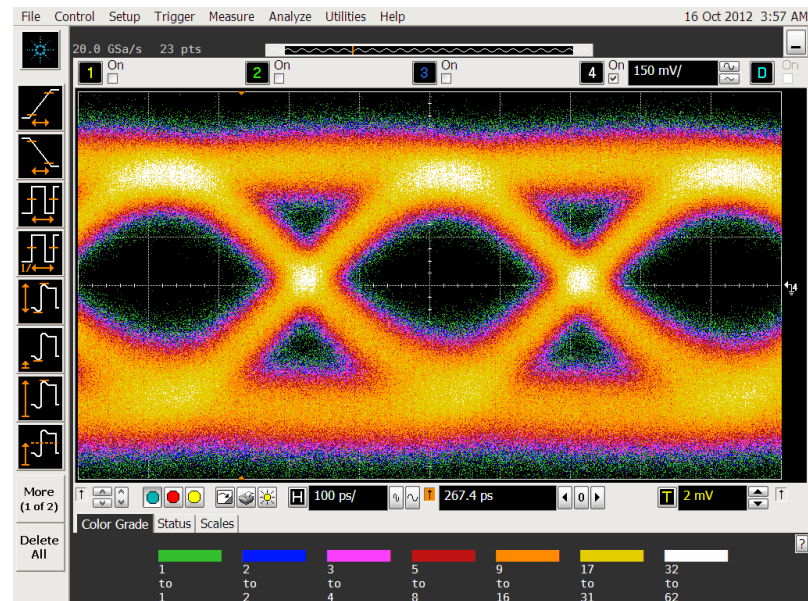


- Split-supply used for sub-bit pre-emphasis
  - Use core and I/O voltage – no regulators

# First modulation in 45nm process

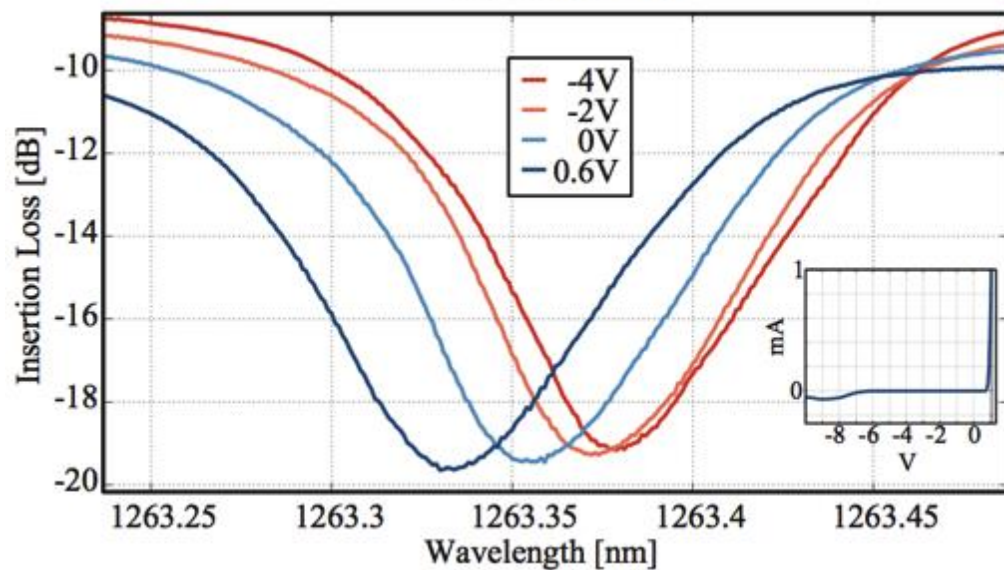
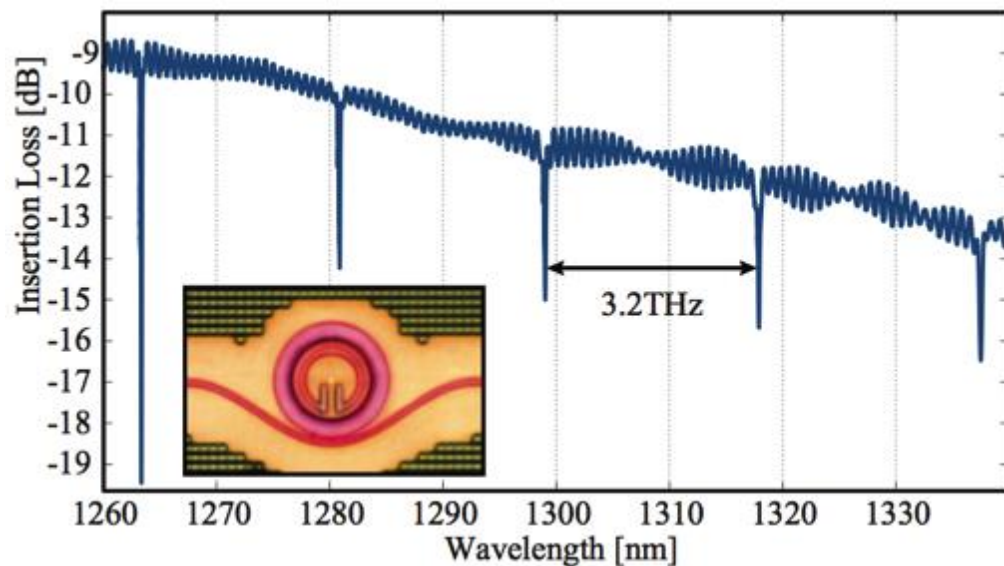
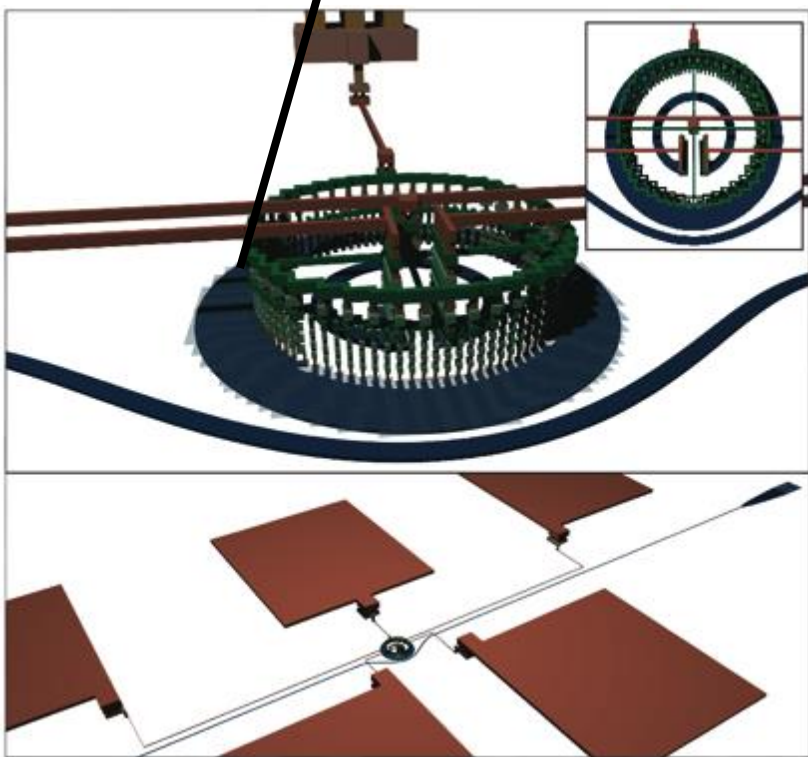
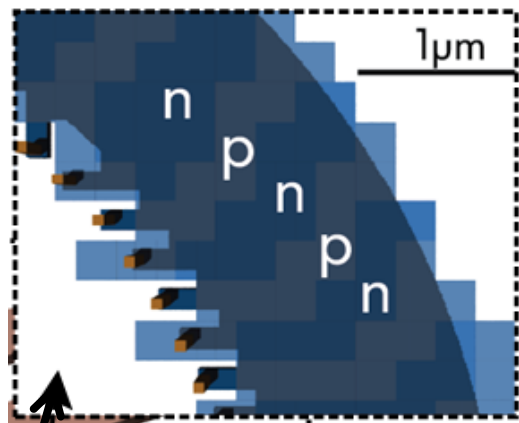


- 2.5Gb/s modulation
- 1.2pJ/bit
- 3dB insertion loss
- 3dB extinction ratio

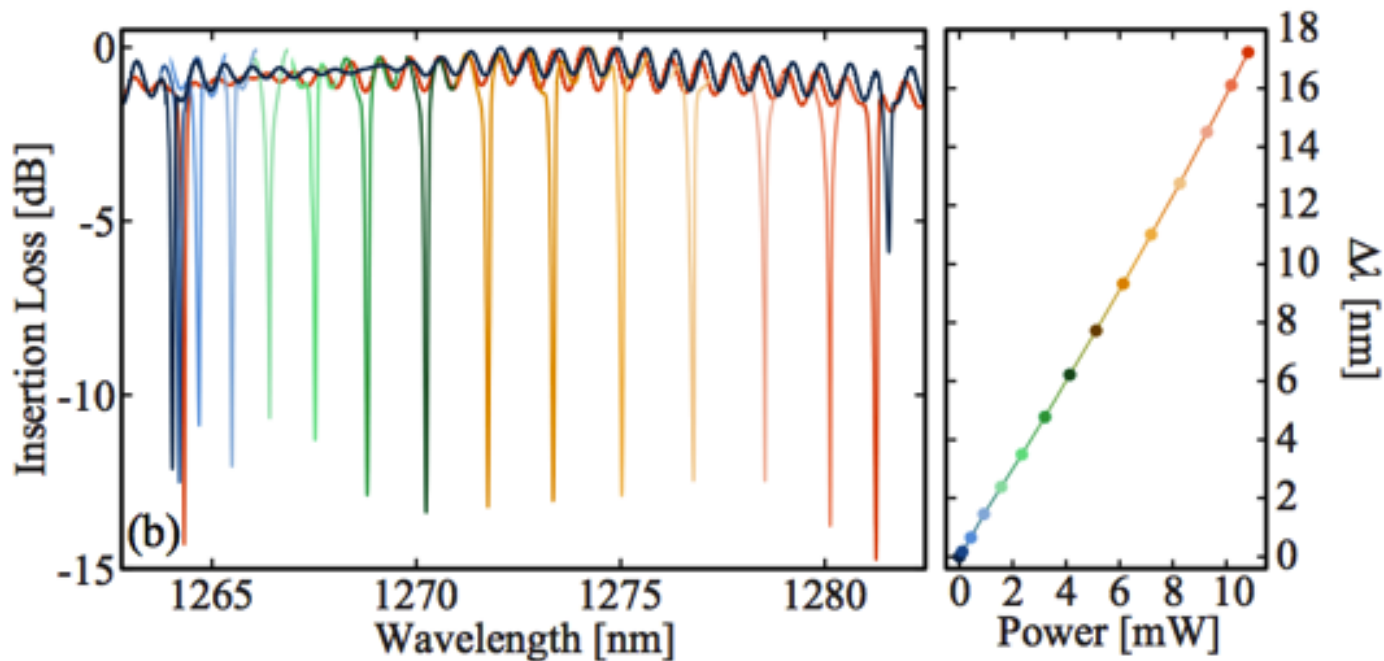


**Moss ISSCC2013**

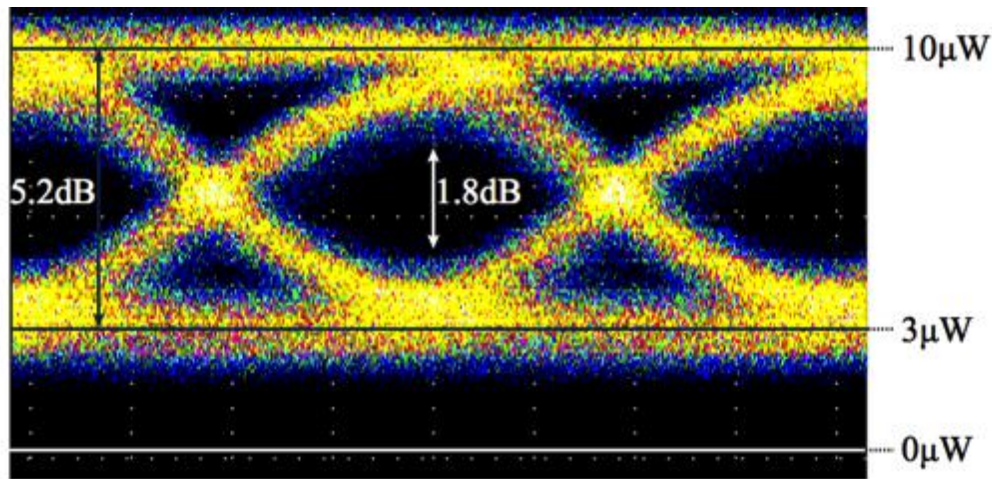
# Depletion modulators in 45nm SOI CMOS



# Depletion modulators in 45nm SOI CMOS



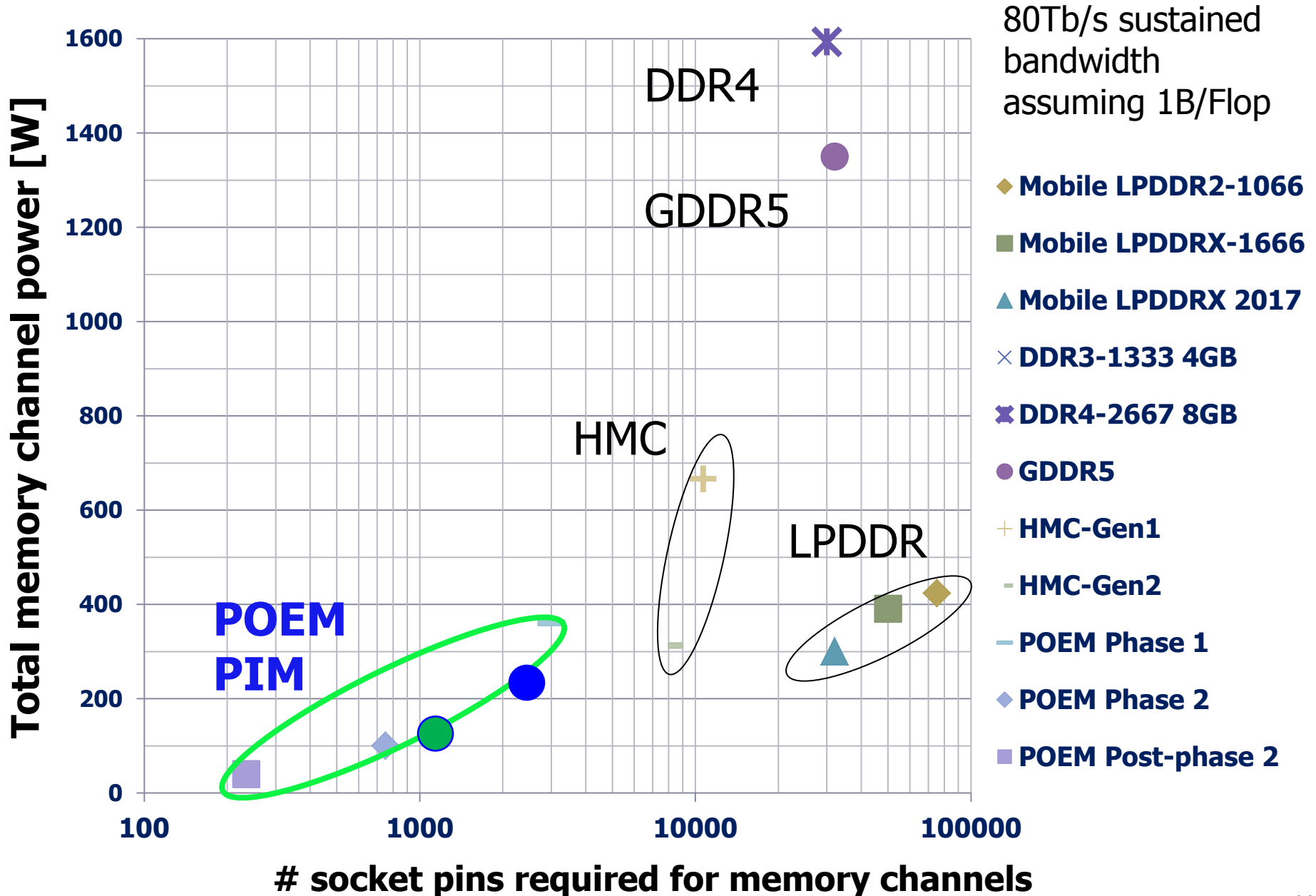
- Modulation:
  - 5 Gbps
  - 5.2dB extinction ratio
- Energy:
  - 55 fJ/bit
  - Tunable across FSR with 400GHz/mW ( $\sim 2\text{nm/mW}$ )







# Power and pins required for 10TFlop/s





# Summary

- Silicon-photonics can push both critical dimensions
  - Energy-efficiency – monolithic integration
  - Bandwidth Density - dense WDM
- Need to optimize across layers
  - Connect devices to circuits, and links to networks
- Building early technology development platforms
  - Feedback to device and circuit designers
  - Accelerated adoption
- EOS Platform designed for multi-project wafer runs
  - Best end-of-line passives in sub-100nm process (3-4dB/cm loss)
  - sub-100fJ/b transmitters/receivers
  - Record-high tuning efficiency with undercut ~ 25uW/K

# Conclusions

- Silicon-photonics – enabler of new capabilities
  - Think “new on-chip inductor” or “new on-chip t-line”
- Potentially revolutionize many applications despite slowdown in CMOS scaling
  - VLSI compute and network infrastructure
  - Wireless comm
  - Imaging and Sensing
- Need process, device, circuit and system-level understanding
- So, jump-in and ride the “new wave”

